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Lee

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(54) **SEMICONDUCTOR CHIPS HAVING REDISTRIBUTED POWER/GROUND LINES DIRECTLY CONNECTED TO POWER/GROUND LINES OF INTERNAL CIRCUITS AND METHODS OF FABRICATING THE SAME**

6,008,543 A 12/1999 Iwabuchi
6,211,576 B1 4/2001 Shimizu et al.
6,235,552 B1 * 5/2001 Kwon et al. 438/106
6,590,295 B1 * 7/2003 Liao et al. 257/781
7,096,581 B2 * 8/2006 Thomas et al. 29/841

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FOREIGN PATENT DOCUMENTS
JP 10-261663 9/1998
KR 2003-0006915 1/2003
KR 2004-0006744 1/2004

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(*) Notice: Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 574 days.

OTHER PUBLICATIONS
English language abstract of Korean Publication No. 2003-0006915.
English language abstract of Korean Publication No. 2004-0006744.
English language abstract of Japanese Publication No. 10-261663.

(21) Appl. No.: **11/378,899**

* cited by examiner

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(65) **Prior Publication Data**

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(57) **ABSTRACT**

(30) **Foreign Application Priority Data**

Mar. 18, 2005 (KR) 10-2005-0022787

Provided are embodiments of semiconductor chips having a redistributed metal interconnection directly connected to power/ground lines of an internal circuit are provided. Embodiments of the semiconductor chips include an internal circuit formed on a semiconductor substrate. A chip pad is disposed on the semiconductor substrate. The chip pad is electrically connected to the internal circuit through an internal interconnection. A passivation layer is provided over the chip pad. A redistributed metal interconnection is provided on the passivation layer. The redistributed metal interconnection directly connects the internal interconnection to the chip pad through a via-hole and a chip pad opening, which penetrate at least the passivation layer. Methods of fabricating the semiconductor chip are also provided.

(51) **Int. Cl.**

H01L 23/52 (2006.01)

(52) **U.S. Cl.** 257/734; 257/758; 257/781

(58) **Field of Classification Search** 257/734, 257/758, 781

See application file for complete search history.

(56) **References Cited**

U.S. PATENT DOCUMENTS

5,774,340 A * 6/1998 Chang et al. 361/771

15 Claims, 19 Drawing Sheets

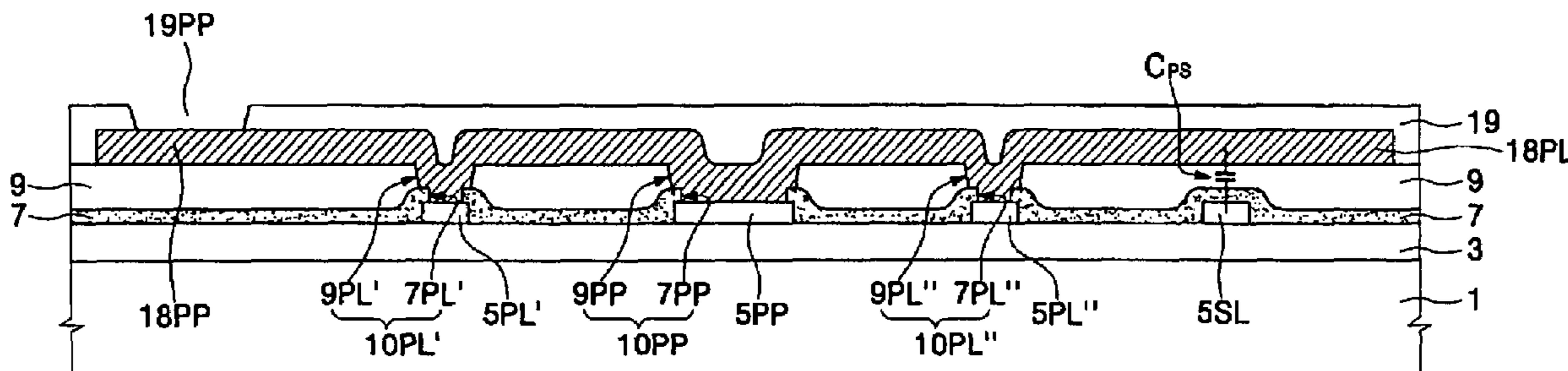


FIG. 2C

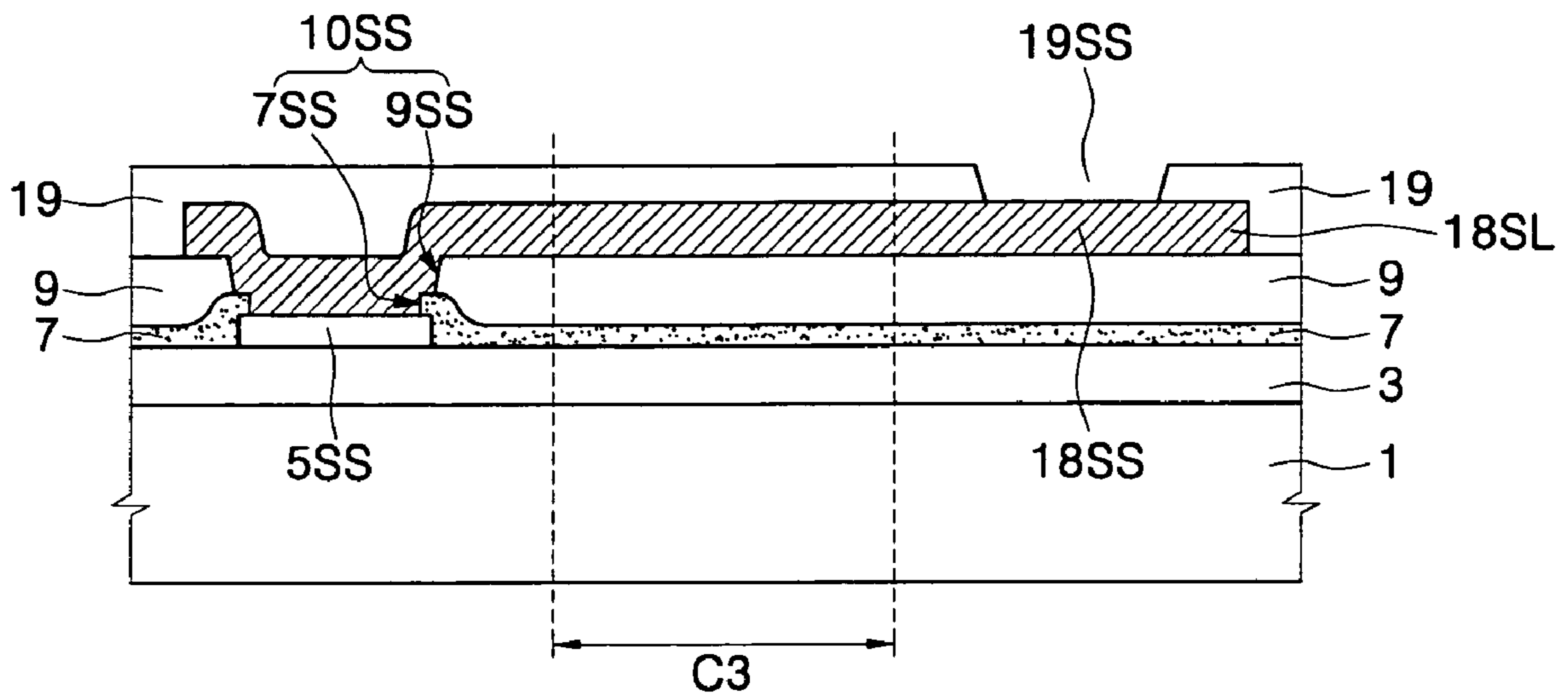


FIG. 3

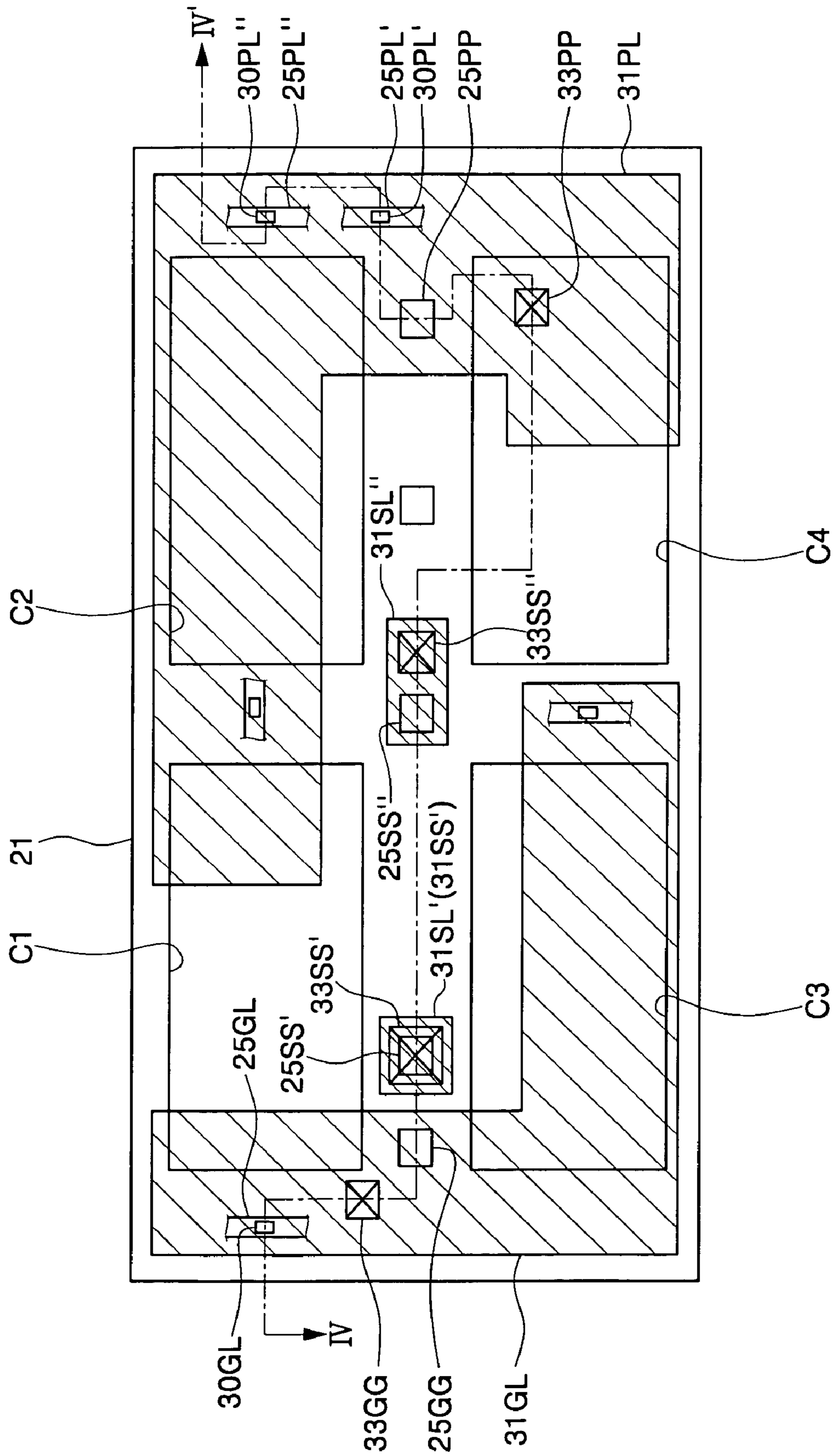


FIG. 7A

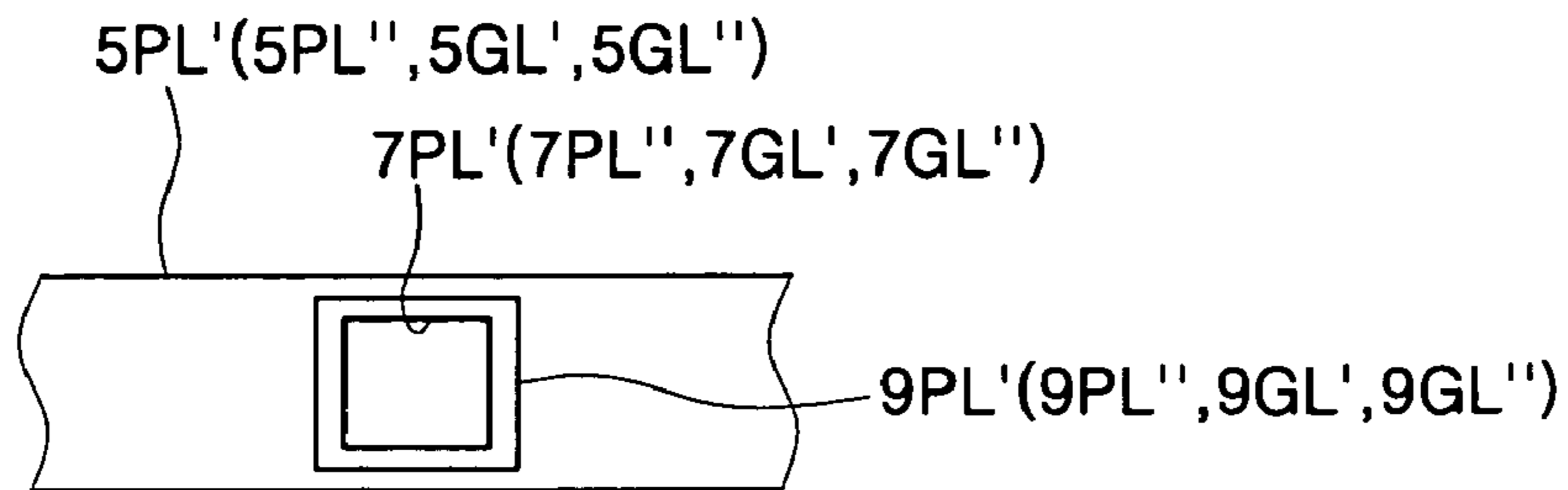


FIG. 7B

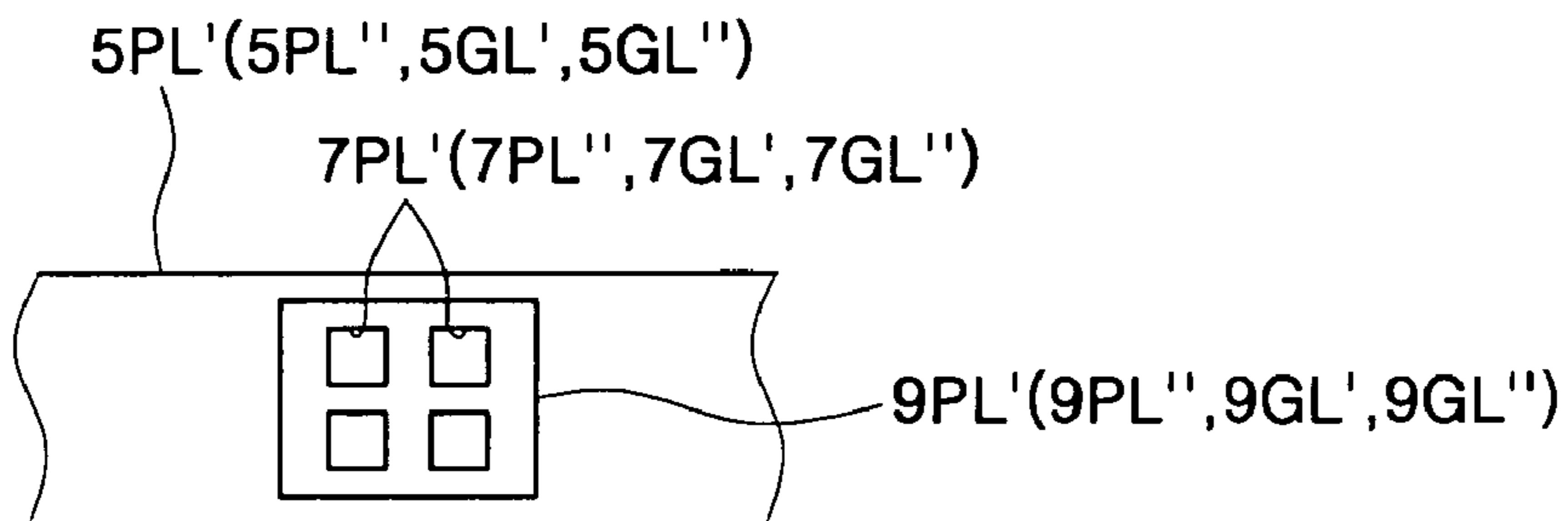


FIG. 7C

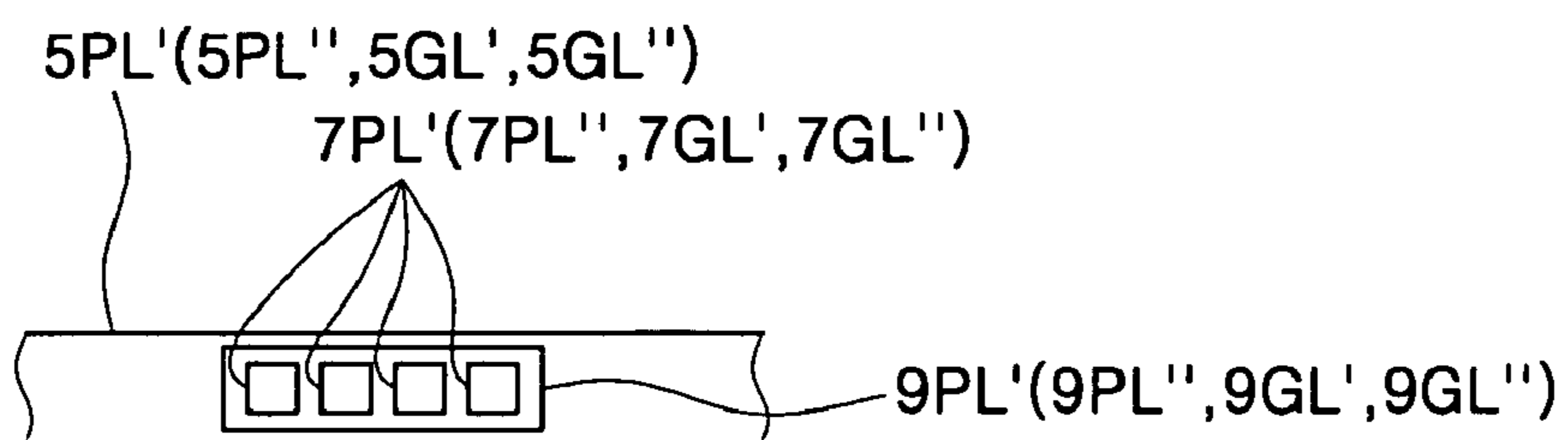


FIG. 8

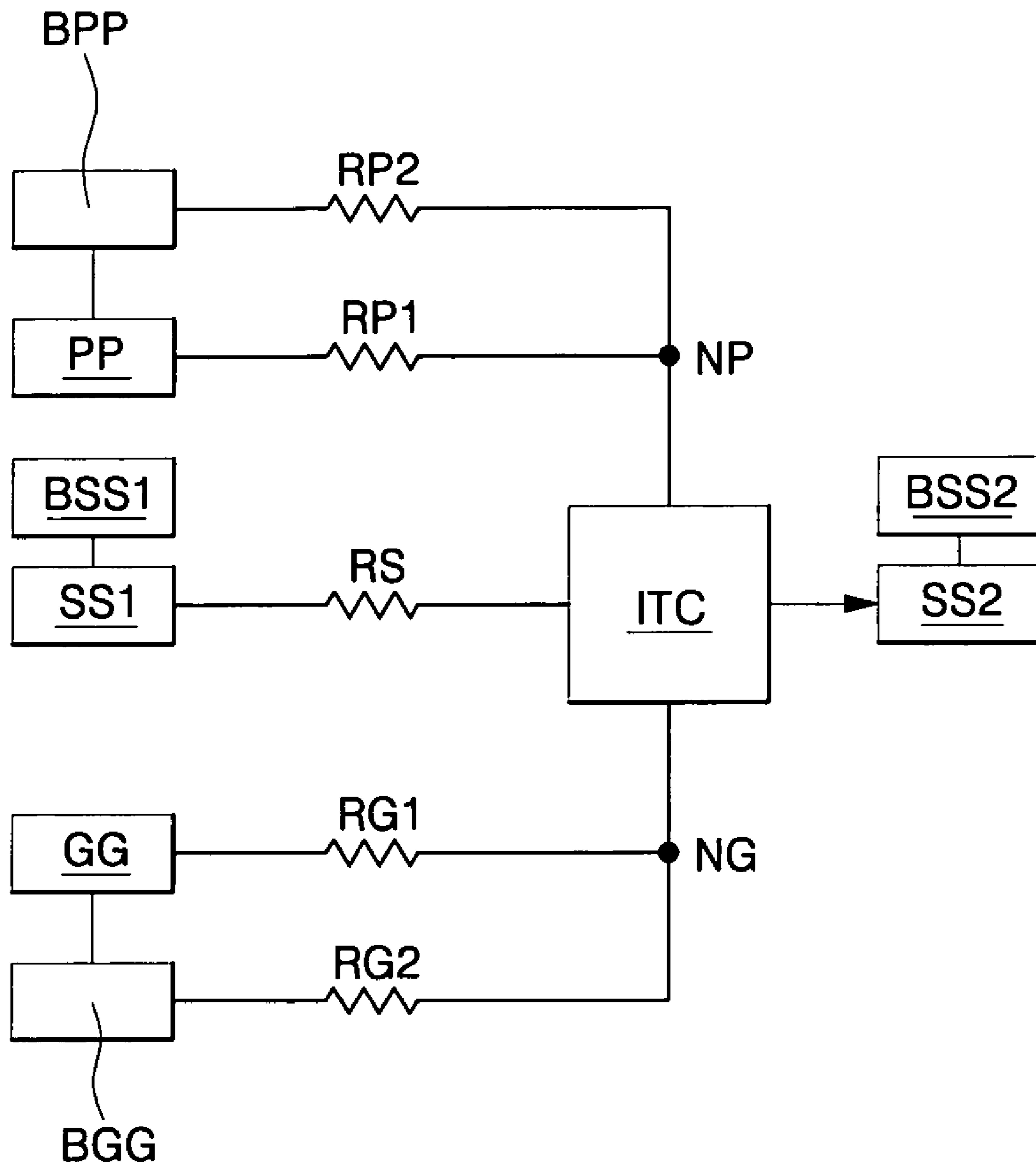


FIG. 9A

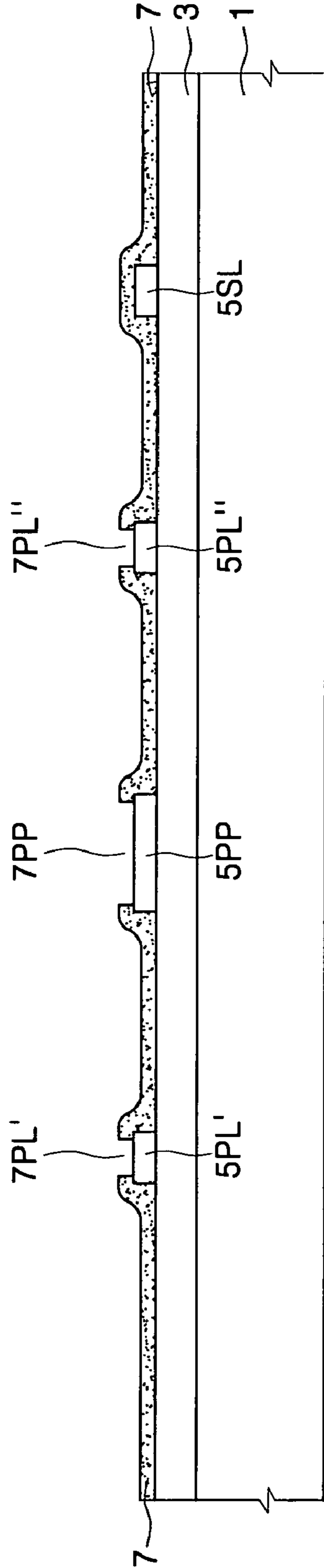


FIG. 9B

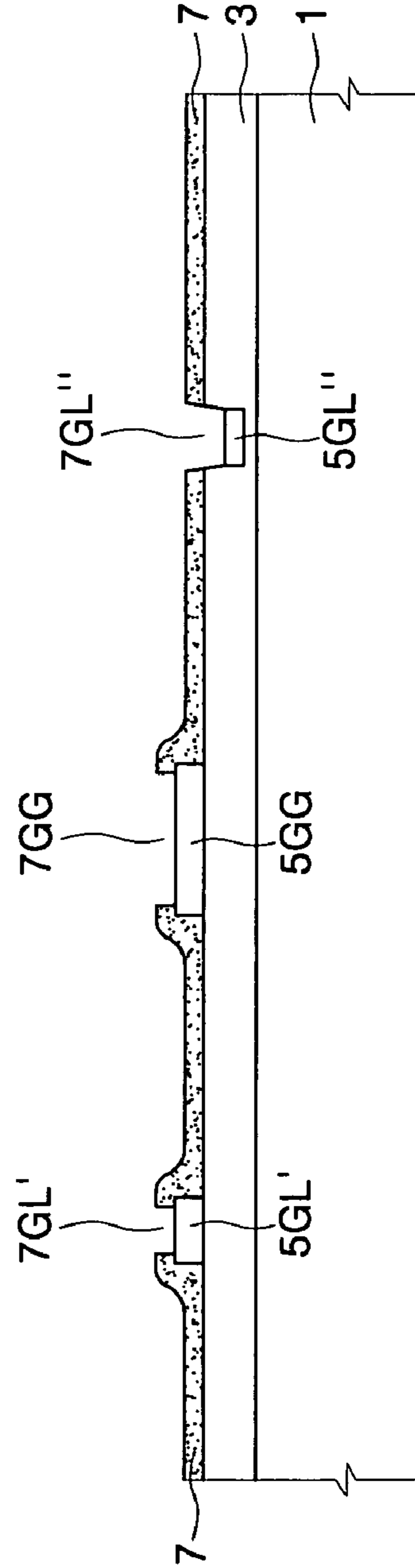


FIG. 9C

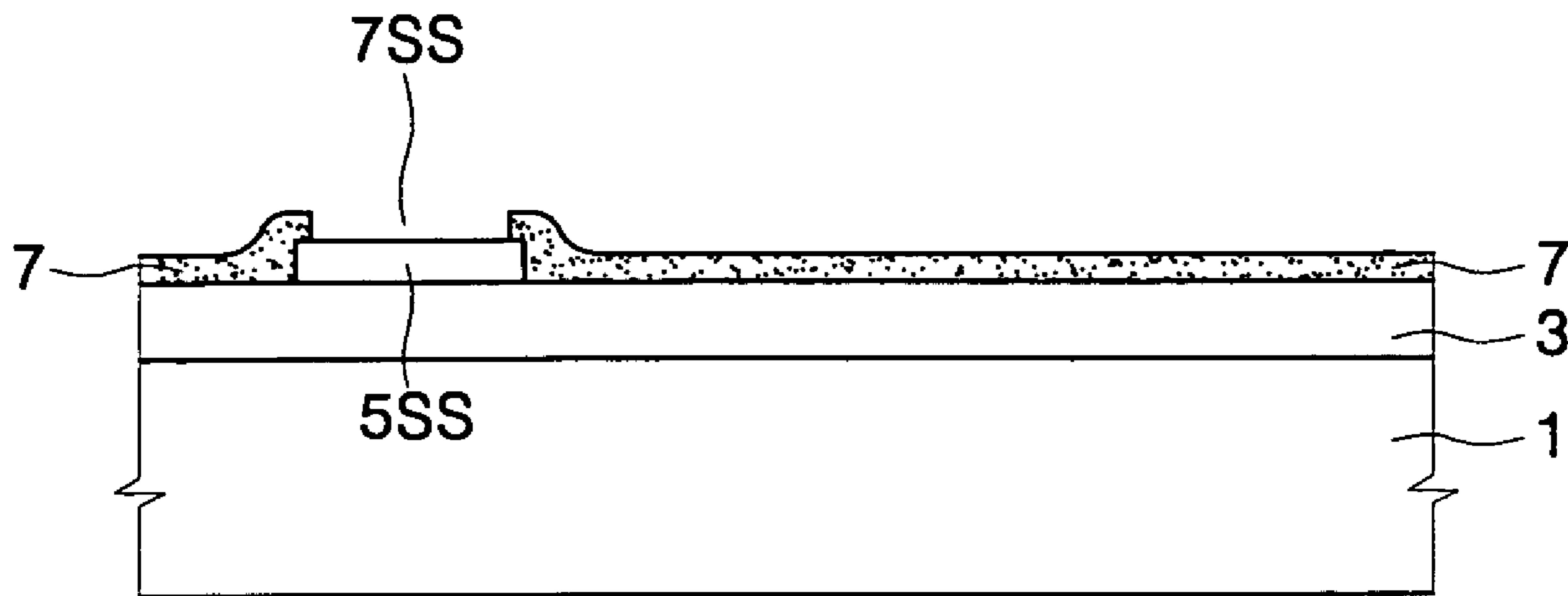


FIG. 10C

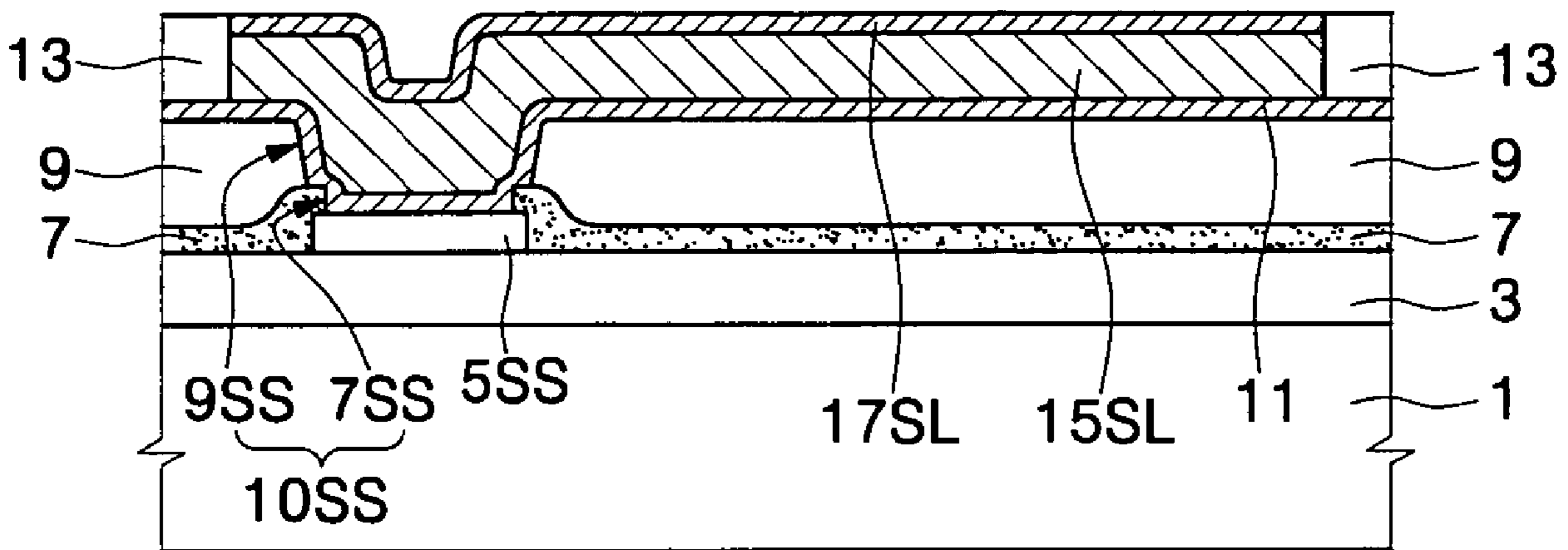


FIG. 11A

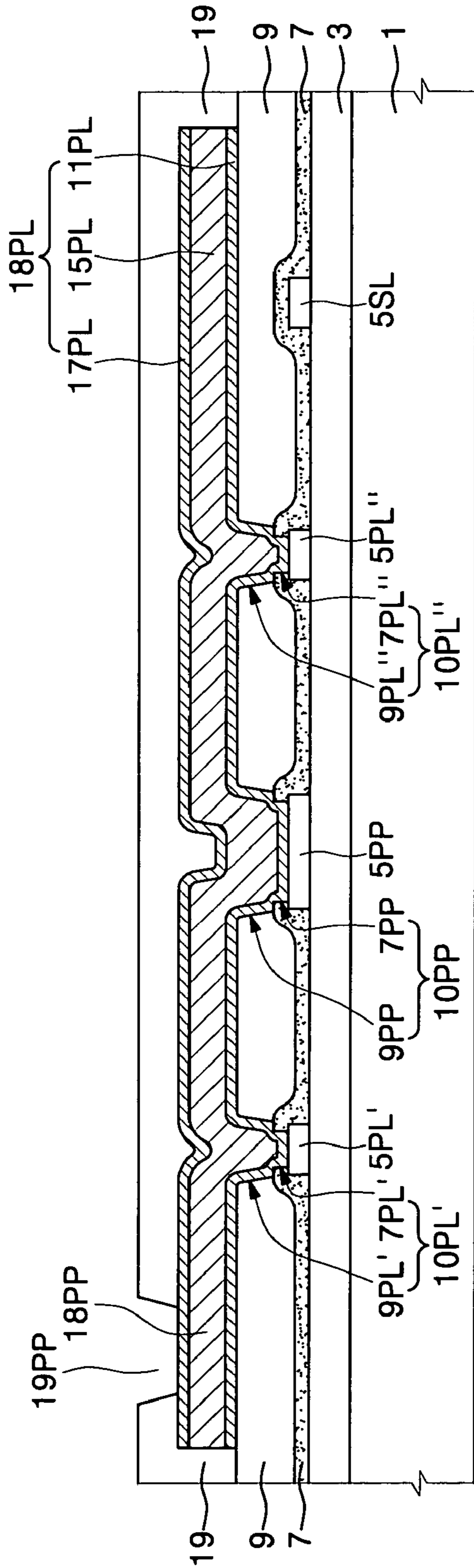


FIG. 11B

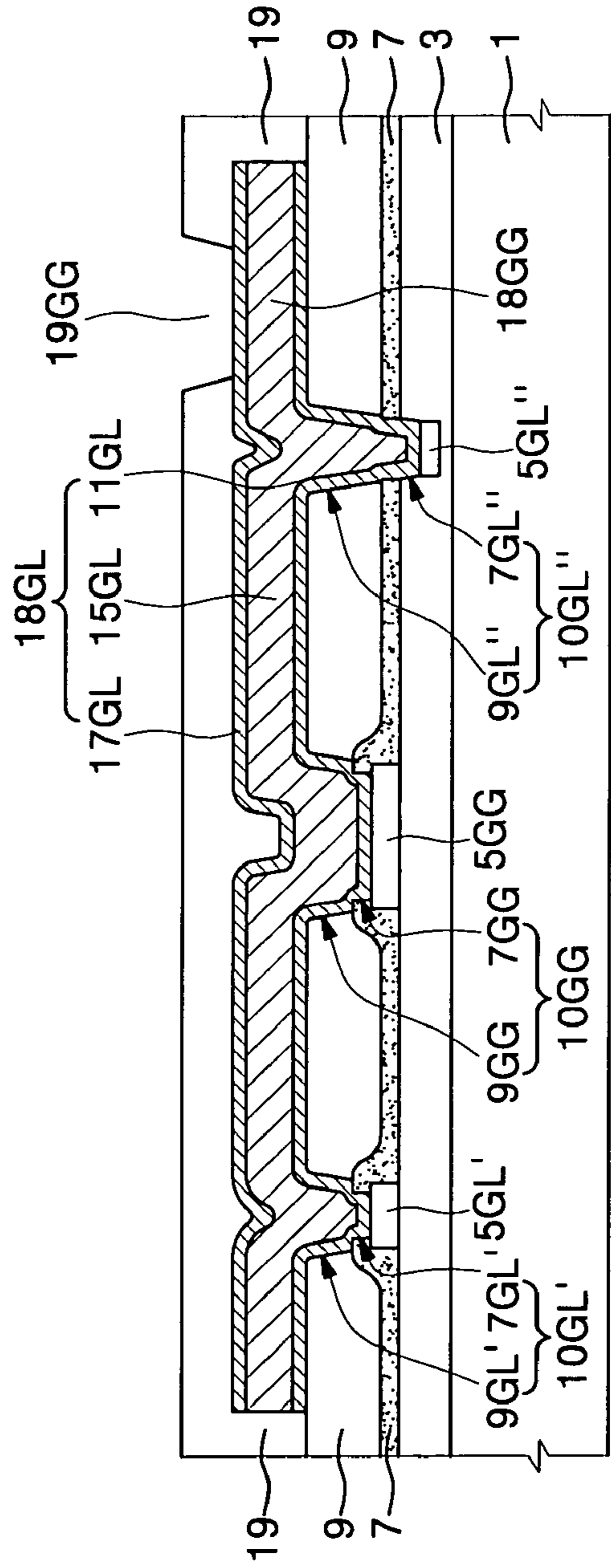


FIG. 11C

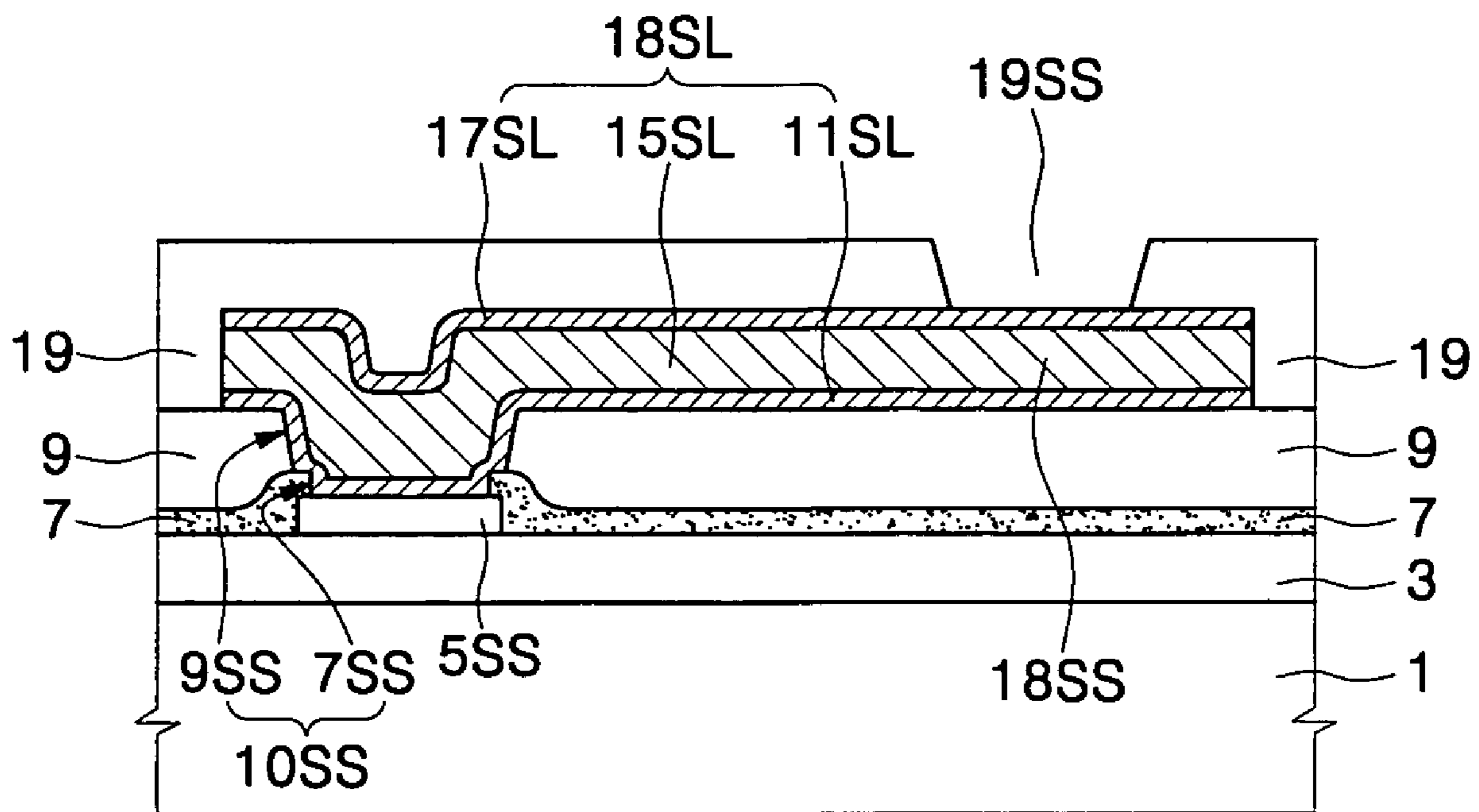


FIG. 12

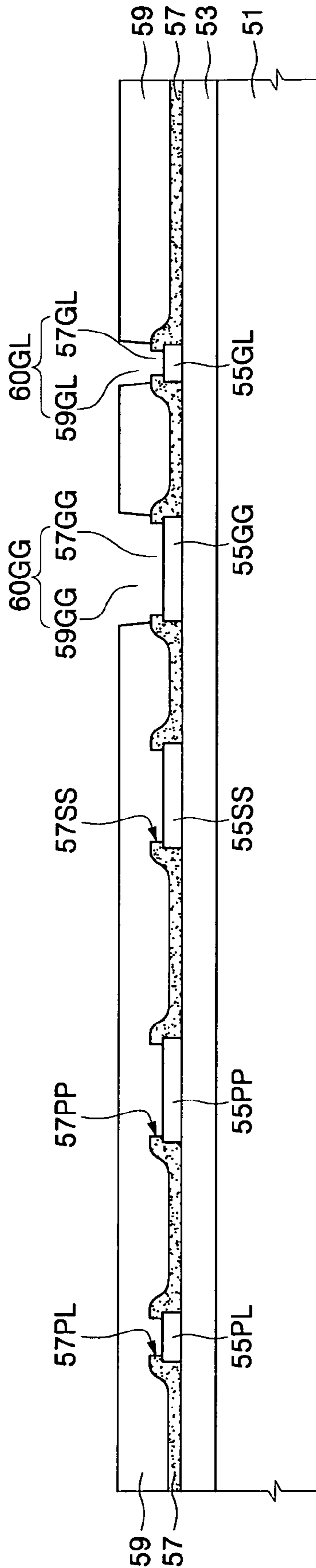
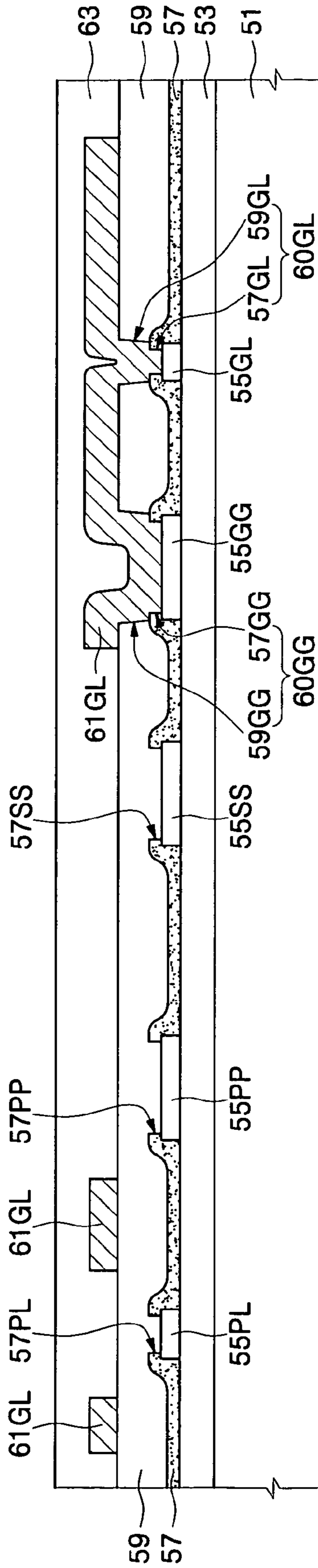


FIG. 13



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**SEMICONDUCTOR CHIPS HAVING
REDISTRIBUTED POWER/GROUND LINES
DIRECTLY CONNECTED TO
POWER/GROUND LINES OF INTERNAL
CIRCUITS AND METHODS OF
FABRICATING THE SAME**

This application claims the benefit of Korean Patent Application No. 2005-0022787, filed Mar. 18, 2005, the disclosure of which is hereby incorporated herein by reference in their entirety.

FIELD OF THE INVENTION

The present invention relates to semiconductor chips and methods of fabricating the same and, more particularly, to semiconductor chips having redistributed power/ground lines directly connected to power/ground lines of internal circuits and methods of fabricating the same.

BACKGROUND OF THE INVENTION

As portable electronic devices become smaller, the dimensions of semiconductor chip packages must be reduced. In order to reduce the dimensions of the semiconductor chip packages, various packaging technologies have been developed. In addition, in order to implement high-performance requirements for the semiconductor chip packages, it may be required to form bonding pads in contact with solder balls or bonding wires at desired positions, regardless of the chip pad locations formed on a semiconductor chip. In this case, the bonding pads are electrically connected to the chip pads through redistributed metal interconnections.

A semiconductor chip having redistributed metal interconnections is disclosed in U.S. Pat. No. 6,211,576 B1 to Shimizu, et al., entitled "Semiconductor Device". According to Shimizu, et al., a power wiring section, a ground wiring section, and a signal wiring section are provided at the same level, and the power wiring section or the ground wiring section is formed adjacent to both sides of at least one portion of the signal wiring section.

SUMMARY

In one embodiment, the invention is directed to semiconductor chips having a redistributed metal interconnection. The semiconductor chips of this embodiment include an internal circuit and a chip pad formed on a semiconductor substrate. The chip pad is electrically connected to the internal circuit through an internal interconnection. A passivation layer is provided over the chip pad and the internal interconnection. A redistributed metal interconnection is provided on the passivation layer. The redistributed metal interconnection is directly connected to the internal interconnection and the chip pad through a via-hole and a chip pad opening, respectively, which penetrate the passivation layer.

BRIEF DESCRIPTION OF THE DRAWINGS

The foregoing and other objects, features, and advantages of the invention will be apparent from the detailed description of exemplary embodiments of the invention, as illustrated in the accompanying drawings. The drawings are not necessarily to scale, emphasis instead is placed upon illustrating the principles of the invention.

FIG. 1 is a plan view illustrating a semiconductor chip in accordance with an embodiment of the present invention.

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FIG. 2A is a cross-sectional view taken along line I-I' of FIG. 1.

FIG. 2B is a cross-sectional view taken along line II-II' of FIG. 1.

5 FIG. 2C is a cross-sectional view taken along line III-III' of FIG. 1.

FIG. 3 is a plan view illustrating a semiconductor chip in accordance with another embodiment of the present invention.

10 FIG. 4 is a cross-sectional view taken along line IV-IV' of FIG. 3.

FIG. 5 is a plan view illustrating a semiconductor chip in accordance with still another embodiment of the present invention.

15 FIG. 6 is a cross-sectional view taken along line V-V' of FIG. 5.

FIG. 7A is a plan view illustrating an exemplary shape of upper/lower internal power via-holes and upper/lower internal ground via-holes shown in FIGS. 1, 3, and 5.

20 FIG. 7B is a plan view illustrating another exemplary shape of upper/lower internal power via-holes and upper/lower internal ground via-holes shown in FIGS. 1, 3, and 5.

FIG. 7C is a plan view illustrating still another exemplary shape of upper/lower internal power via-holes and upper/lower internal ground via-holes shown in FIGS. 1, 3, and 5.

25 FIG. 8 is a schematic equivalent circuit diagram of semiconductor chips in accordance with embodiments of the present invention.

30 FIGS. 9A, 10A, and 11A are cross-sectional views taken along line I-I' of FIG. 1 to illustrate methods of fabricating a semiconductor chip in accordance with an embodiment of the present invention.

35 FIGS. 9B, 10B, and 11B are cross-sectional views taken along line II-II' of FIG. 1 to illustrate methods of fabricating a semiconductor chip in accordance with an embodiment of the present invention.

40 FIG. 9C, 10C, and 11C are cross-sectional views taken along line III-III' of FIG. 1 to illustrate methods of fabricating a semiconductor chip in accordance with an embodiment of the present invention.

45 FIGS. 12 to 15 are cross-sectional views taken along line V-V' of FIG. 5 to illustrate methods of fabricating a semiconductor chip in accordance with another embodiment of the present invention.

DETAILED DESCRIPTION

The present invention will now be described more fully hereinafter with reference to the accompanying drawings, in which exemplary embodiments of the invention are shown. This invention may, however, be embodied in different forms and should not be construed as limited to the embodiments set forth herein. Rather, these embodiments are provided so that this disclosure is thorough and complete and fully conveys the scope of the invention to those skilled in the art. In the drawings, the thicknesses of layers and regions are exaggerated for clarity. The same reference numerals are used to denote the same elements throughout the specification.

60 FIG. 1 is a plan view of a semiconductor chip in accordance with an embodiment of the present invention, and FIGS. 2A, 2B, and 2C are cross-sectional views taken along lines I-I', II-II', and III-III' of FIG. 1, respectively.

65 Referring to FIGS. 1, 2A, 2B, and 2C, an internal circuit (not shown) is provided on a semiconductor substrate 1. The internal circuit may be memory cells and/or a peripheral circuit of a semiconductor memory device. For example, the internal circuit may be DRAM cells and/or a peripheral cir-

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cuit for driving the DRAM cells. In this case, the DRAM cells may be disposed in a plurality of cell array regions, i.e., first to fourth cell array regions C1, C2, C3 and C4. However, the present invention is not limited to DRAM devices, but may be applicable to various other semiconductor devices. For example, the cell array regions C1, C2, C3, and C4 may be SRAM cell array regions or flash memory cell array regions. In addition, the present invention may also be applicable to a non-memory semiconductor device.

An interlayer insulating layer 3 is provided on the substrate 1 having the internal circuit. At least one internal interconnection and at least one chip pad are disposed on the interlayer insulating layer 3. The chip pad may be electrically connected to the internal circuit, through the internal interconnection. The internal interconnection may include first and second internal power lines 5PL' and 5PL", which supply a power voltage to the internal circuit as well as first and second internal ground lines 5GL' and 5GL", which supply a ground voltage to the internal circuit. In this case, the chip pad may include a power chip pad 5PP and a ground chip pad 5GG. The power chip pad 5PP is electrically connected to a power supply terminal of the internal circuit through the first and second internal power lines 5PL' and 5PL", and the ground chip pad 5GG is electrically connected to a ground supply terminal of the internal circuit through the first and second internal ground lines 5GL' and 5GL". In addition, the internal interconnection may further include an internal signal line 5SL electrically connected to an input or output terminal of the internal circuit. In this case, the chip pad may further include a signal chip pad 5SS electrically connected to the input or output terminal of the internal circuit through the internal signal line 5SL.

All the internal interconnections 5PL', 5PL", 5GL', 5GL", and 5SL may be disposed on the interlayer insulating layer 3. Alternatively, at least one of the internal interconnections 5PL', 5PL", 5GL', 5GL", and 5SL may be disposed in or under the interlayer insulating layer 3. For example, the second internal ground line 5GL" may be provided in the interlayer insulating layer 3 as shown in FIG. 2B. In other words, at least one of the internal interconnections 5PL', 5PL", 5GL', 5GL", and 5SL may be an interconnection formed of a different metal layer from the chip pads 5PP, 5GG, and 5SS.

A passivation layer 7 may be provided on the substrate 1 having the internal interconnections 5PL', 5PL", 5GL', 5GL", and 5SL and the chip pads 5PP, 5GG, and 5SS. The passivation layer 7 is a material layer for protecting the internal circuit from external moisture and physical impact. In general, the passivation layer 7 may include a silicon oxide layer and a silicon nitride layer, which are sequentially stacked. Predetermined regions of the internal power lines 5PL' and 5PL" and the first internal ground line 5GL' may be exposed through a first lower power via-hole 7PL', a second lower power via-hole 7PL", and a first lower ground via-hole 7GL', which penetrate the passivation layer 7, respectively. In addition, the power chip pad 5PP, the ground chip pad 5GG, and the signal chip pad 5SS may be exposed through a lower power chip pad opening 7PP, a lower ground chip pad opening 7GG, and a lower signal chip pad opening 7SS, which penetrate the passivation layer 7, respectively. Further, when any one of the internal interconnections, e.g., the second internal ground line 5GL" is disposed in the interlayer insulating layer 3 as described above, the second internal ground line 5GL" may be exposed through a second lower ground via-hole 7GL" which penetrates the passivation layer 7 and the interlayer insulating layer 3.

A first dielectric layer 9 is provided on the substrate 1 having the lower via-holes 7PL', 7PL", 7GL', and 7GL" and

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the lower chip pad openings 7PP, 7GG, and 7SS. The first dielectric layer 9 may be a polymer layer such as a polyimide layer or a photosensitive polyimide layer. Alternatively, the first dielectric layer 9 may be an oxide layer such as a silicon oxide layer. The internal power lines 5PL' and 5PL" and the internal ground lines 5GL' and 5GL" may be respectively exposed through first and second upper power via-holes 9PL' and 9PL" and first and second upper ground via-holes 9GL' and 9GL" which penetrate the first dielectric layer 9. Further, the power chip pad 5PP, the ground chip pad 5GG, and the signal chip pad 5SS may be respectively exposed through an upper power chip pad opening 9PP, an upper ground chip pad opening 9GG, and an upper signal chip pad opening 9SS which penetrate the first dielectric layer 9.

The first lower power via-hole 7PL' and the first upper power via-hole 9PL' constitute a first power via-hole 10PL', and the second lower power via-hole 7PL" and the second upper power via-hole 9PL" constitute a second power via-hole 10PL". In addition, the first lower ground via-hole 7GL' and the first upper ground via-hole 9GL' constitute a first ground via-hole 10GL', and the second lower ground via-hole 7GL" and the second upper ground via-hole 9GL" constitute a second ground via-hole 10GL". Further, the lower power chip pad opening 7PP and the upper power chip pad opening 9PP constitute a power chip pad opening 10PP, and the lower ground chip pad opening 7GG and the upper ground chip pad opening 9GG constitute a ground chip pad opening 10GG. Furthermore, the lower signal chip pad opening 7SS and the upper signal chip pad opening 9SS constitute a signal chip pad opening 10SS.

A redistributed metal interconnection is provided on the first dielectric layer 9. The redistributed metal interconnection may include a redistributed power line 18PL, a redistributed ground line 18GL, and a redistributed signal line 18SL. The redistributed power line 18PL directly connects the internal power lines 5PL' and 5PL" to the power chip pad 5PP through the first and second power via-holes 10PL' and 10PL" and the power chip pad opening 10PP, and the redistributed ground line 18GL directly connects the internal ground lines 5GL' and 5GL" to the ground chip pad 5GG through the first and second ground via-holes 10GL' and 10GL" and the ground chip pad opening 10GG. The redistributed signal line 18SL is electrically connected to the signal chip pad 5SS through the signal chip pad opening 10SS.

Consequently, the redistributed power line 18PL provides an additional power voltage supply path in addition to the internal power lines 5PL' and 5PL" supplying a power voltage to the internal circuit. Therefore, a stable power voltage can be supplied to the internal circuit due to the presence of the redistributed power line 18PL. In particular, the lower the electrical resistance of the redistributed power line 18PL is, the more stable the power voltage of the internal circuit is. Similarly, the redistributed ground line 18GL provides an additional ground voltage supply path in addition to the internal ground lines 5GL' and 5GL" supplying a ground voltage to the internal circuit. Therefore, a stable ground voltage can be supplied to the internal circuit due to the presence of the redistributed ground line 18GL. In particular, the lower the electrical resistance of the redistributed ground line 18GL is, the more stable the ground voltage of the internal circuit is.

Each of the redistributed power line 18PL, the redistributed ground line 18GL, and the redistributed signal line 18SL may include a copper layer having relatively low resistivity as compared to an aluminum layer and a tungsten layer. In other embodiments, each of the redistributed metal interconnections 18PL, 18GL, and 18SL may include a seed metal layer and a main metal layer, which are sequentially stacked. The

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main metal layer may include a copper layer. In detail, the main metal layer may include a copper layer, a diffusion barrier layer, and a gold layer, which are sequentially stacked. The gold layer is a metal layer for improving adhesion between the redistributed metal interconnections **18PL**, **18GL**, and **18SL** and bonding wires contacting the redistributed metal interconnections **18PL**, **18GL**, and **18SL**, and the diffusion barrier layer is a metal layer for suppressing interaction between the copper layer and the gold layer. In addition, the diffusion barrier layer may act as an oxidation stopping layer for preventing the copper layer from being oxidized when the copper layer is exposed to the air. The diffusion barrier layer may be, for example, a nickel layer.

When the main metal layer includes a copper layer, the seed metal layer may include a seed wetting layer and a seed copper layer, which are sequentially stacked. The seed wetting layer is a metal layer for improving adhesion of the seed copper layer. For example, the seed wetting layer may be a titanium layer or a chrome layer.

The redistributed metal interconnections **18PL**, **18GL**, and **18SL** may have a plane shape as shown in FIG. 1 when viewed from a plan view. Alternatively, the redistributed metal interconnections **18PL**, **18GL**, and **18SL** may have a mesh shape.

A portion of the internal signal line **5SL** may overlap the redistributed power line **18PL** and/or the redistributed ground line **18GL** when viewed from a plan view. For example, the internal signal line **5SL** may overlap the redistributed power line **18PL** as shown in FIGS. 1 and 2A. In this case, parasitic capacitance C_{ps} may exist between the internal signal line **5SL** and the redistributed power line **18PL**. The parasitic capacitance C_{ps} may cause a time delay of a signal transmitted through the internal signal line **5SL**. However, according to the embodiments, the parasitic capacitance C_{ps} can be remarkably reduced since the first dielectric layer **9** is relatively thicker than the interlayer insulating layer **3**. For example, when the first dielectric layer **9** is formed of a polymer layer and the interlayer insulating layer **3** is formed of a silicon oxide layer, the thickness of the first dielectric layer **9** ranges from about 2 μm to about 20 μm while the thickness of the interlayer insulating layer **3** ranges from about 0.3 μm to about 1.3 μm . Therefore, the signal delay time due to the parasitic capacitance C_{ps} is negligible.

The substrate **1** having the redistributed power line **18PL**, the redistributed ground line **18GL**, and the redistributed signal line **18SL** may be covered with a second dielectric layer **19**. The second dielectric layer **19** may be a polymer layer such as a polyimide layer or a photosensitive polyimide layer. Alternatively, the second dielectric layer **19** may be an oxide layer such as a silicon oxide layer. The redistributed power line **18PL** may be exposed by at least one power bonding pad opening **19PP** that penetrates the second dielectric layer **19**, and the redistributed ground line **18GL** may be exposed by at least one ground bonding pad opening **19GG** that penetrates the second dielectric layer **19**. In addition, the redistributed signal line **18SL** may be exposed by at least one signal bonding pad opening **19SS** that penetrates the second dielectric layer **19**. As a result, the power bonding pad opening **19PP**, the ground bonding pad opening **19GG**, and the signal bonding pad opening **19SS** define a power bonding pad **18PP**, a ground bonding pad **18GG**, and a signal bonding pad **18SS**, respectively. The number of the signal bonding pads **19SS** may be equal to the number of the signal chip pads **5SS**. On the other hand, the number of the power bonding pad openings **19PP** may be equal to or different from the number of the power chip pads **5PP**, and the number of the ground

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bonding pad openings **19GG** may be equal to or different from the number of the ground chip pads **5GG**.

Bonding wires for conventional packaging may be bonded onto the bonding pads **18PP**, **18GG**, and **18SS**. Alternatively, balls (or bumps) for wafer level packaging may be provided on the bonding pads **18PP**, **18GG**, and **18SS**.

According to the above-described embodiments, the chip pads **5PP**, **5GG**, and **5SS** are disposed on a straight line crossing the center of the semiconductor substrate **1**, and the bonding pads **18PP**, **18GG**, and **18SS** are disposed at edges of the semiconductor substrate **1**. That is, the bonding pad openings **19PP**, **19GG**, and **19SS** may be spaced apart from the chip pads **5PP**, **5GG** and **5SS**, respectively, when viewed from a plan view. Therefore, in accordance with the above embodiments, center-type pads may be converted to edge-type pads as shown in FIG. 1. On the contrary, the chip pads **5PP**, **5GG**, and **5SS** may be disposed at edges, i.e., along a periphery, of the semiconductor substrate **1**, and the bonding pads **18PP**, **18GG**, and **18SS** may be disposed on a straight line crossing the center of the semiconductor substrate **1**. Accordingly, one skilled in the art will appreciate that edge-type pads may be converted to center-type pads.

In accordance with another embodiment of the present invention, the bonding pad openings **19PP**, **19GG**, and **19SS** may overlap the chip pads **5PP**, **5GG**, and **5SS**, respectively, when viewed from a plan view. In this case, when the chip pads **5PP**, **5GG**, and **5SS** are center-type pads as shown in FIG. 1, the bonding pads **18PP**, **18GG**, and **18SS** may also be center-type pads.

FIG. 3 is a plan view of a semiconductor chip in accordance with yet another embodiment of the present invention, and FIG. 4 is a cross-sectional view taken along line IV-IV' of FIG. 3. Although the embodiment is described in conjunction with a semiconductor memory device having first to fourth cell array regions **C1**, **C2**, **C3**, and **C4**, it will be apparent to those skilled in the art that the present invention may be equally applicable to a non-memory semiconductor device. In addition, the embodiment is different from the embodiment described with reference to FIGS. 1, 2A, 2B, and 2C in terms of positions of the bonding pads. That is, center-type pads may be converted to random-type pads.

Referring to FIGS. 3 and 4, an interlayer insulating layer **23** is provided on a semiconductor substrate **21**. A power chip pad **25PP**, a ground chip pad **25GG** and signal chip pads **25SS'** and **25SS''** as well as internal power lines **25PL'** and **25PL''**, an internal ground line **25GL** and at least one internal signal line (not shown) are provided on the interlayer insulating layer **23**. However, at least one of the internal power lines **25PL'** and **25PL''**, the internal ground line **25GL**, and the internal signal line may be disposed in or under the interlayer insulating layer **23**. That is, the chip pads **25PP**, **25GG**, **25SS'**, and **25SS''** and the internal interconnections **25PL'**, **25PL''**, and **25GL** may have the same or similar configuration and structure as the embodiments described with reference to FIGS. 1, 2A, 2B, and 2C. A passivation layer **27** is provided on the substrate **21** having the chip pads **25PP**, **25GG**, **25SS'**, and **25SS''** and the internal interconnections **25PL'**, **25PL''**, and **25GL**. The passivation layer **27** may be the same or similar material layer as the passivation layer **7** described with reference to FIGS. 2A, 2B, and 2C.

Like the embodiment described with reference to FIGS. 1, 2A, 2B, and 2C, the passivation layer **27** may have a lower power chip pad opening **27PP**, a lower ground chip pad opening **27GG**, a first lower signal chip pad opening **27SS'**, a second lower signal chip pad opening **27SS''**, a first lower power via-hole **27PL'**, a second lower power via-hole **27PL''**, and a lower ground via-hole **27GL**, which expose the chip

pads **25PP**, **25GG**, **25SS'**, and **25SS''** and the internal interconnections **25PL'**, **25PL''**, and **25GL**, respectively.

A first dielectric layer **29** is provided on the substrate **21** having the passivation layer **27**. The first dielectric layer **29** may also be the same or similar material layer as the first dielectric layer **9** described with reference to FIGS. **2A**, **2B**, and **2C**. The first dielectric layer **29** may have an upper power chip pad opening **29PP**, an upper ground chip pad opening **29GG**, a first upper signal chip pad opening **29SS'**, a second upper signal chip pad opening **29SS''**, a first upper power via-hole **29PL'**, a second upper power via-hole **29PL''**, and an upper ground via-hole **29GL**, which expose the chip pads **25PP**, **25GG**, **25SS'**, and **25SS''** and the internal interconnections **25PL'**, **25PL''**, and **25GL**, respectively.

The lower power chip pad opening **27PP** and the upper power chip pad opening **29PP** constitute a power chip pad opening **30PP**, and the lower ground chip pad opening **27GG** and the upper ground chip pad opening **29GG** constitute a ground chip pad opening **30GG**. In addition, the first lower signal chip pad opening **27SS'** and the first upper signal chip pad opening **29SS'** constitute a first signal chip pad opening **30SS'**, and the second lower signal chip pad opening **27SS''** and the second upper signal chip pad opening **29SS''** constitute a second signal chip pad opening **30SS''**. Further, the first lower power via-hole **27PL'** and the first upper power via-hole **29PL'** constitute a first power via-hole **30PL'**, and the second lower power via-hole **27PL''** and the second upper power via-hole **29PL''** constitute a second power via-hole **30PL''**. Furthermore, the lower ground via-hole **27GL** and the upper ground via-hole **29GL** constitute a ground via-hole **30GL**.

At least one redistributed metal interconnection is provided on the first dielectric layer **29**. The redistributed metal interconnection may include a redistributed power line **31PL**, a redistributed ground line **31GL**, a first redistributed signal line **31SL'** and a second redistributed signal line **31SL''**. The redistributed power line **31PL** directly connects the internal power lines **25PL'** and **25PL''** to the power chip pad **25PP** through the power via-holes **30PL'** and **30PL''** and the power chip pad opening **30PP**, and the redistributed ground line **31GL** directly connects the internal ground line **25GL** to the ground chip pad **25GG** through the ground via-hole **30GL** and the ground chip pad opening **30GG**. The first redistributed signal line **31SL'** is electrically connected to the first signal chip pad **25SS'** through the first signal chip pad opening **30SS'**, and the second redistributed signal line **31SL''** is electrically connected to the second signal chip pad **25SS''** through the second signal chip pad opening **30SS''**.

Consequently, the redistributed power line **31PL** provides an additional power voltage supply path in addition to the internal power lines **25PL'** and **25PL''** supplying a power voltage to the internal circuit, and the redistributed ground line **31GL** provides an additional ground voltage supply path in addition to the internal ground lines **25GL** supplying a ground voltage to the internal circuit. Therefore, stable power and ground voltages can be supplied to the internal circuit due to the presence of the redistributed power line **31PL** and the redistributed ground line **31GL**.

The redistributed power line **31PL**, the redistributed ground line **31GL**, and the redistributed signal lines **31SL'** and **31SL''** may be the same material layer as the redistributed metal interconnections **18PL**, **18GL**, and **18SL** described with reference to FIGS. **2A**, **2B**, and **2C**. In addition, the redistributed power line **31PL**, the redistributed ground line **31GL** and the redistributed signal lines **31SL'** and **31SL''** may have the same configuration as the redistributed metal interconnections **18PL**, **18GL**, and **18SL** described with reference to FIGS. **2A**, **2B**, and **2C**. That is, the redistributed power line

31PL, the redistributed ground line **31GL** and the redistributed signal lines **31SL'** and **31SL''** may have a plane shape or a mesh shape, when viewed from a plan view.

The substrate having the redistributed power line **31PL**, the redistributed ground line **31GL** and the redistributed signal lines **31SL'** and **31SL''** may be covered with a second dielectric layer **33**. The second dielectric layer **33** may be a polymer layer such as a polyimide layer or a photosensitive polyimide layer. Alternatively, the second dielectric layer **33** may be a silicon oxide layer. The redistributed power line **31PL** may be exposed by at least one power bonding pad opening **33PP** that penetrates the second dielectric layer **33**, and the redistributed ground line **31GL** may be exposed by at least one ground bonding pad opening **33GG** that penetrates the second dielectric layer **33**. In addition, the redistributed signal lines **31SL'** and **31SL''** may be each exposed by first and second signal bonding pad openings **33SS'** and **33SS''** that penetrate the second dielectric layer **33**. Consequently, the power bonding pad opening **33PP**, the ground bonding pad opening **33GG**, the first signal bonding pad opening **33SS'**, and the second signal bonding pad opening **33SS''** define a power bonding pad **31PP**, a ground bonding pad **31GG**, a first signal bonding pad **31SS'**, and a second signal bonding pad **31SS''**, respectively. The number of the signal bonding pads **33SS'** and **33SS''** may be equal to the number of the signal chip pads **25SS'** and **25SS''**. On the other hand, the number of the power bonding pad openings **33PP** may be equal to or different from the number of the power chip pads **25PP**, and the number of the ground bonding pad openings **33GG** may be equal to or different from the number of the ground chip pads **25GG**.

Bonding wires for conventional packaging may be bonded onto the bonding pads **31PP**, **31GG**, **31SS'**, and **31SS''**. Alternatively, balls for wafer level packaging may be located on the bonding pads **31PP**, **31GG**, **31SS'**, and **31SS''**.

In accordance with the above-described embodiments, the chip pads **25PP**, **25GG**, **25SS'**, and **25SS''** are disposed on a straight line crossing the center of the semiconductor substrate **1**, whereas the bonding pads **31PP**, **31GG**, **31SS'**, and **31SS''** may be randomly disposed in the semiconductor substrate **1**. That is, center-type pads may be converted to random-type pads as shown in FIG. **3**. On the contrary, the chip pads **25PP**, **25GG**, **25SS'**, and **25SS''** may be randomly disposed in the semiconductor substrate **1**, and the bonding pads **31PP**, **31GG**, **31SS'**, and **31SS''** may be disposed on a straight line crossing the center of the semiconductor substrate **1**. In this case, it will be apparent to those skilled in the art that random-type pads may be converted to center-type pads.

In still other embodiments of the present invention, the chip pads **25PP**, **25GG**, **25SS'**, and **25SS''** may be disposed at edges of the semiconductor substrate **1**, and the bonding pads **31PP**, **31GG**, **31SS'**, and **31SS''** may be randomly disposed in the semiconductor substrate **1**. In this case, it will be apparent to those skilled in the art that edge-type pads may be converted to random-type pads. On the contrary, the chip pads **25PP**, **25GG**, **25SS'**, and **25SS''** may be randomly disposed in the semiconductor substrate **1**, and the bonding pads **31PP**, **31GG**, **31SS'**, and **31SS''** may be disposed at edges of the semiconductor substrate **1**. In this case, it will be apparent to those skilled in the art that random-type pads may be converted to edge-type pads.

FIG. **5** is a plan view of a semiconductor chip in accordance with yet another embodiment of the present invention, and FIG. **6** is a cross-sectional view taken along line V-V' of FIG. **5**. Although the embodiment is described in conjunction with a semiconductor memory device having a cell array region C,

it will be apparent to those skilled in the art that the present invention may be equally applicable to a non-memory semiconductor device.

Referring to FIGS. 5 and 6, an interlayer insulating layer 53 is provided on a semiconductor substrate 51. First and second power supply chip pads 55GG and 55PP, a signal chip pad 55SS, and first and second internal power supply lines 55GL and 55PL are provided on the interlayer insulating layer 53. In addition, at least one internal signal line (not shown) may be provided on the interlayer insulating layer 53. The first and second power supply chip pads 55GG and 55PP may be a ground chip pad and a power chip pad, respectively. In this case, the first and second internal power supply lines 55GL and 55PL correspond to an internal ground line and an internal power line, respectively. On the contrary, the first and second power supply chip pads 55GG and 55PP may be a power chip pad and a ground chip pad, respectively. In this case, the first and second internal power supply lines 55GL and 55PL correspond to an internal power line and an internal ground line, respectively.

In another embodiment of the present invention, at least one of the first and second internal power supply lines 55GL and 55PL and the internal signal line may be disposed in or under the interlayer insulating layer 53. That is, the internal power supply lines 55GL and 55PL and the internal signal line may have the same or similar configuration and structure as the embodiments described with reference to FIGS. 1, 2A, 2B, and 2C. A passivation layer 57 is provided on the substrate 51 having the chip pads 55GG, 55PP, and 55SS and the internal interconnections 55GL and 55PL. The passivation layer 57 may be the same or similar material layer as the passivation layer 7 described with reference to FIGS. 2A, 2B, and 2C.

Like the embodiments described with reference to FIGS. 1, 2A, 2B, and 2C, the passivation layer 57 has a first lower power supply chip pad opening 57GG, a second lower power supply chip pad opening 57PP, a lower signal chip pad opening 57SS, a first lower via-hole 57GL, and a second lower via-hole 57PL, which expose the chip pads 55GG, 55PP, and 55SS and the internal interconnections 55GL and 55PL, respectively.

A first lower dielectric layer 59 is provided on the substrate 51 having the passivation layer 57. The first lower dielectric layer 59 may also be the same or similar material layer as the first dielectric layer 9 described with reference to FIGS. 2A, 2B, and 2C. The first lower dielectric layer 59 has a first upper power supply chip pad opening 59GG and a first upper via-hole 59GL, which expose the first power supply chip pad 55GG and the first internal power supply line 55GL, respectively. The first lower power supply chip pad opening 57GG and the first upper power supply chip pad opening 59GG constitute a first power supply chip pad opening 60GG, and the first lower via-hole 57GL and the first upper via-hole 59GL constitute a first via-hole 60GL.

A first redistributed power supply line 61GL is provided on the first lower dielectric layer 59. The first redistributed power supply line 61GL directly connects the first internal power supply line 55GL to the first power supply chip pad 55GG through the first via-hole 60GL and the first power supply chip pad opening 60GG. The first redistributed power supply line 61GL may be the same or similar material layer as the redistributed metal interconnections 18PL, 18GL, and 18SL described with reference to FIGS. 2A, 2B, and 2C. In addition, the first redistributed power supply line 61GL may have the same or similar configuration as the redistributed metal interconnections 18PL, 18GL, and 18SL described with reference to FIGS. 2A, 2B, and 2C. That is, the first redistributed

power supply line 61GL may have a plane shape or a mesh shape, when viewed from a plan view.

A first upper dielectric layer 63 is provided over the first redistributed power supply line 61GL. The first upper dielectric layer 63 may also be the same or similar material layer as the first dielectric layer 9 described with reference to FIGS. 2A, 2B, and 2C. The first upper/lower dielectric layers 63 and 59 have a second upper power supply chip pad opening 63PP and a second upper via-hole 63PL that expose the second power supply chip pad 55PP and the second internal power supply line 55PL, respectively. The second lower power supply chip pad opening 57PP and the second upper power supply chip pad opening 63PP constitute a second power supply chip pad opening 64PP, and the second lower via-hole 57PL and the second upper via-hole 63PL constitute a second via-hole 64PL.

A second redistributed power supply line 65PL is provided over the first upper dielectric layer 63. The second redistributed power supply line 65PL directly connects the second internal power supply line 55PL to the second power supply chip pad 55PP through the second via-hole 64PL and the second power supply chip pad opening 64PP. The second redistributed power supply line 65PL may be the same or similar material layer as the first redistributed power supply line 61GL. In addition, the second redistributed power supply line 65PL may have the same or similar configuration as the first redistributed power supply line 61GL. That is, the second redistributed power supply line 65PL may have a plane shape or a mesh shape, when viewed from a plan view.

When the first and second power supply chip pads 55GG and 55PP are a ground chip pad and a power chip pad respectively, the first and second redistributed power supply lines 61GL and 65PL correspond to a redistributed ground line and a redistributed power line respectively. On the contrary, when the first and second power supply chip pads 55GG and 55PP are a power chip pad and a ground chip pad respectively, the first and second redistributed power supply lines 61GL and 65PL correspond to a redistributed power line and a redistributed ground line, respectively.

In some embodiments, at least a portion of the first redistributed power supply line 61GL may overlap at least a portion of the second redistributed power supply line 65PL, as shown in the plan view of FIG. 5. In this case, power capacitance C_{pg} (see FIG. 6) may be provided between the first and second redistributed power supply lines 61GL and 65PL. The power capacitance C_{pg} can improve power noise immunity. Therefore, in order to increase the power noise immunity, it is preferable that the overlap area between the first and second redistributed power supply lines 61GL and 65PL be increased.

Consequently, it is possible to improve noise immunity and stability of the ground and power signals, which are applied to an internal circuit (i.e., memory cells in the cell array region C or peripheral circuits adjacent to the cell array region C).

The substrate 51 having the second redistributed power supply line 65PL may be covered with a second dielectric layer 67. The second dielectric layer 67 may be a polymer layer such as a polyimide layer or a photosensitive polyimide layer. Alternatively, the second dielectric layer 67 may be an oxide layer such as a silicon oxide layer. The first redistributed power supply line 61GL may be exposed by at least one first bonding pad opening 67GG that penetrates the second dielectric layer 67 and the first upper dielectric layer 63, and the second redistributed power supply line 65PL may be exposed by at least one second bonding pad opening 67PP that penetrates the second dielectric layer 67. That is, the first bonding pad opening 67GG defines a first bonding pad 61GG,

and the second bonding pad opening 67PP defines a second bonding pad 65PP. The first and second bonding pads 61GG and 65PP may also be in direct contact with bonding wires or balls.

Although not shown in the FIGS. 5 and 6, the signal chip pad 55SS may be electrically connected to a redistributed signal line which is provided on the first lower dielectric layer 59 or the first upper dielectric layer 63, and the redistributed signal line may be exposed by a signal bonding pad opening, which penetrates the first upper dielectric layer 63 and the second dielectric layer 67 or penetrates only the second dielectric layer 67.

The bonding pad openings 67PP and 67GG may also overlap the chip pads 55PP and 55GG, respectively. Alternatively, the bonding pad openings 67PP and 67GG may be spaced apart from the chip pads 55PP and 55GG, when viewed from a plan view. That is, the embodiment may also provide semiconductor chips having various pad positions.

FIGS. 7A to 7C are plan views illustrating various configurations of the lower via-holes 7PL', 7PL", 7GL', and 7GL" and the upper via-holes 9PL', 9PL", 9GL', and 9GL" which expose the internal interconnections 5PL', 5PL", 5GL', and 5GL" shown in FIGS. 1, 2A, 2B, and 2C.

Referring to FIG. 7A, each of the lower via-holes 7PL', 7PL", 7GL', and 7GL" may have a single rectangular shape, and each of the upper via-holes 9PL', 9PL", 9GL', and 9GL" may also have a single rectangular shape. In this case, the upper via-holes 9PL', 9PL", 9GL', and 9GL" may be larger in size than the lower via-holes 7PL', 7PL", 7GL', and 7GL". Alternatively, each of the lower via-holes 7PL', 7PL", 7GL', and 7GL" may include a plurality of lower sub via-holes which are two-dimensionally arrayed as shown in FIG. 7B, and each of the upper via-holes 9PL', 9PL", 9GL', and 9GL" may have the same or similar configuration as shown in FIG. 7A. In this case, the upper via-holes 9PL', 9PL", 9GL', and 9GL" may have a sufficient width to overlap all of the lower sub via-holes.

When the internal interconnections 5PL', 5PL", 5GL', and 5GL" have smaller widths than those shown in FIGS. 7A and 7B, each of the lower via-holes 7PL', 7PL", 7GL', and 7GL" may include a plurality of lower sub via-holes which are one-dimensionally arrayed along a longitudinal direction of the internal interconnections 5PL', 5PL", 5GL', and 5GL" as shown in FIG. 7C. In this case, each of the upper via-holes 9PL', 9PL", 9GL', and 9GL" may have a rectangular shape to fully overlap the lower sub via-holes.

It will be apparent to those skilled in the art that the lower via-holes 7PL', 7PL", 7GL', and 7GL" and the upper via-holes 9PL', 9PL", 9GL', and 9GL" shown in FIGS. 7A, 7B, and 7C may also be applicable to the embodiments shown in FIGS. 3 to 6.

FIG. 8 is a schematic equivalent circuit diagram of a semiconductor chip in accordance with embodiments of the present invention.

Referring to FIG. 8, a power terminal NP of an internal circuit ITC of the semiconductor chips in accordance with some embodiments of the present invention is electrically connected to a power chip pad PP (5PP in FIG. 1, 25PP in FIG. 3, or 55PP in FIG. 5) through internal power lines (5PL' and 5PL" in FIG. 1, 25PL' and 25PL" in FIG. 3, or 55PL in FIG. 5) corresponding to a first power resistor RP1. In addition, the power terminal NP of the internal circuit ITC is electrically connected to a redistributed power line (18PL in FIG. 1, 31PL in FIG. 3, or 65PL in FIG. 5) corresponding to a second power resistor RP2, and the redistributed power line 18PL, 31PL, or 65PL is electrically connected to the power chip pad PP (5PP, 25PP, or 55PP). The redistributed power

line 18PL, 31PL, or 65PL includes a power bonding pad BPP (18PP in FIG. 2A, 31PP in FIG. 4, or 65PP in FIG. 6) to which an external power voltage is applied. Consequently, the first power resistor RP1 and the second power resistor RP2 are connected in parallel to each other between the power bonding pad BPP and the power terminal NP. Therefore, when an external power voltage is applied to the power bonding pad BPP, the external power voltage is supplied to the power terminal NP through the first and second power resistors RP1 and RP2 which are connected in parallel. The second power resistor RP2 is a metal layer such as a copper layer having a low resistivity and a large plane area, as described above. Therefore, the second power resistor RP2 may exhibit remarkably low electrical resistance as compared to the first power resistor RP1. As a result, a stable power voltage can be supplied to the power terminal NP of the internal circuit ITC due to the presence of the second power resistor RP2.

Similarly, a ground terminal NG of an internal circuit ITC of semiconductor chips in accordance with some embodiments of the present invention is electrically connected to a ground chip pad GG (5GG in FIG. 1, 25GG in FIG. 3, or 55GG in FIG. 5) through internal ground lines (5GL' and 5GL" in FIG. 1, 25GL in FIG. 3, or 55GL in FIG. 5) corresponding to a first ground resistor RG1. In addition, the ground terminal NG of the internal circuit ITC is electrically connected to a redistributed ground line (18GL in FIG. 1, 31GL in FIG. 3, or 65GL in FIG. 5) corresponding to a second ground resistor RG2, and the redistributed ground line 18GL, 31GL, or 65GL is electrically connected to the ground chip pad GG (5GG, 25GG, or 55GG). The redistributed ground line 18GL, 31GL, or 65GL includes a ground bonding pad BGG (18GG in FIG. 2A, 31GG in FIG. 4, or 65GG in FIG. 6) to which an external ground voltage is applied. Consequently, the first ground resistor RG1 and the second ground resistor RG2 are connected in parallel to each other between the ground bonding pad BGG and the ground terminal NG. Therefore, when an external ground voltage is applied to the ground bonding pad BGG, the external ground voltage is supplied to the ground terminal NG through the first and second ground resistors RG1 and RG2, which are connected in parallel. The second ground resistor RG2 is a metal layer such as a copper layer having a low resistivity and a large plane area, as described above. Therefore, the second ground resistor RG2 may have remarkably low electrical resistance as compared to the first ground resistor RG1. As a result, a stable ground voltage can be supplied to the ground terminal NG of the internal circuit ITC due to the presence of the second ground resistor RG2.

An input terminal of the internal circuit ITC is electrically connected to a first signal chip pad SS1 (5SS in FIG. 1) through an internal signal line (5SL in FIG. 1) corresponding to a signal resistor RS, and the first signal chip pad SS1 is electrically connected to a redistributed signal line (18SL in FIG. 1). The redistributed signal line 18SL includes a first signal bonding pad BSS1 (18SS in FIG. 2C) to which an external signal is applied. Therefore, when a first input signal is applied to the first signal bonding pad BSS1, the first input signal can be supplied to the input terminal of the internal circuit ITC through the redistributed signal line 18SL, the first signal chip pad SS1 and the internal signal line RS. Further, an output terminal of the internal circuit ITC is electrically connected to a second signal chip pad SS2, and the second signal chip pad SS2 is electrically connected to another redistributed signal line. The other redistributed signal line includes a second signal bonding pad BSS2. Therefore, an output signal of the internal circuit ITC can be output through the second signal chip pad SS2 and the second signal bonding pad BSS2.

Hereinafter, methods of fabricating semiconductor chips in accordance with exemplary embodiments of the present invention will be described.

FIGS. 9A, 10A, and 11A are cross-sectional views taken along line I-I' of FIG. 1 to illustrate methods of fabricating a semiconductor chip in accordance with an embodiment of the present invention, and FIGS. 9B, 10B, and 11B are cross-sectional views taken along line II-II' of FIG. 1 to illustrate methods of fabricating a semiconductor chip in accordance with an embodiment of the present invention. In addition, FIGS. 9C, 10C, and 11C are cross-sectional views taken along line III-III' of FIG. 1 to illustrate methods of fabricating a semiconductor chip in accordance with an embodiment of the present invention.

Referring to FIGS. 9A, 9B, and 9C, an internal circuit (not shown) is formed on a semiconductor substrate 1. The internal circuit may include memory cells of a semiconductor memory device and a peripheral circuit for driving the memory cells. The memory cells may be formed in a plurality of cell array regions, for example, in first to fourth cell array regions (C1, C2, C3, and C4 in FIG. 1). The semiconductor memory device may be a DRAM device. In this case, a plurality of DRAM cells may be two-dimensionally arrayed in the first to fourth cell array regions C1, C2, C3, and C4. Alternatively, the internal circuit may be a non-memory semiconductor device.

An interlayer insulating layer 3 is formed on the substrate 1 having the internal circuit. The interlayer insulating layer 3 may be formed of an oxide layer such as a silicon oxide layer. A metal layer is formed on the interlayer insulating layer 3, and the metal layer is then patterned to form internal interconnections electrically connected to the internal circuit and chip pads electrically connected to the internal interconnections. The internal interconnections may include first and second internal power lines 5PL' and 5PL", first and second internal ground lines 5GL' and 5GL", and an internal signal line 5SL. The internal power lines 5PL' and 5PL" are electrically connected to a power terminal of the internal circuit, and the internal ground lines 5GL' and 5GL" are electrically connected to a ground terminal of the internal circuit. In addition, the internal signal line 5SL is electrically connected to an input terminal or an output terminal of the internal circuit.

The chip pads may include a power chip pad 5PP, a ground chip pad 5GG, and a signal chip pad 5SS. The power chip pad 5PP is electrically connected to the power terminal of the internal circuit through the internal power lines 5PL' and 5PL", and the ground chip pad 5GG is electrically connected to the ground terminal of the internal circuit through the internal ground lines 5GL' and 5GL". In addition, the signal chip pad 5SS is electrically connected to the input terminal or the output terminal of the internal circuit through the internal signal line 5SL.

At least one of the internal interconnections may be formed in or under the interlayer insulating layer 3. For example, the second internal ground line 5GL" may be formed in the interlayer insulating layer 3, as shown in FIG. 9B. In this case, the second internal ground line 5GL" may be formed of a conductive layer different from the chip pads 5PP, 5GG, and 5SS, the internal power lines 5PL' and 5PL", the first internal ground line 5GL', and the internal signal line 5SL.

A passivation layer 7 is formed over the chip pads 5PP, 5GG and 5SS and the internal interconnections 5PL', 5PL", 5GL', 5GL", and 5SL. The passivation layer 7 may be formed by sequentially stacking, for example, a silicon oxide layer and a silicon nitride layer. The passivation layer 7 and the interlayer insulating layer 3 are patterned to form a lower power chip pad opening 7PP, a lower ground chip pad open-

ing 7GG, and a lower signal chip pad opening 7SS, which expose the chip pads 5PP, 5GG, and 5SS, respectively. First and second lower power via-holes 7PL' and 7PL" as well as first and second lower ground via-holes 7GL' and 7GL" may also be formed to respectively expose the internal power lines 5PL' and 5PL" as well as the internal ground lines 5GL' and 5GL" during formation of the lower chip pad openings 7PP, 7GG, and 7SS.

Referring to FIGS. 10A, 10B, and 10C, a first dielectric layer 9 is formed on the substrate 1 having the lower chip pad openings 7PP, 7GG, and 7SS and the lower via-holes 7PL', 7PL", 7GL', and 7GL". The first dielectric layer 9 may be formed of an insulating material having a lower dielectric constant than that of the interlayer insulating layer 3. In addition, the first dielectric layer 9 may be formed to a thickness greater than that of the interlayer insulating layer 3. The first dielectric layer 9 may be formed of a polymer layer such as a polyimide layer or a photosensitive polyimide layer. Alternatively, the first dielectric layer 9 may be formed of an oxide layer such as a silicon oxide layer.

The first dielectric layer 9 is patterned to form an upper power chip pad opening 9PP, an upper ground chip pad opening 9GG, and an upper signal chip pad opening 9SS, which expose the chip pads 5PP, 5GG, and 5SS, respectively. An upper via-hole may be formed to expose at least one of the internal power lines 5PL' and 5PL" and the internal ground lines 5GL' and 5GL" during formation of the upper chip pad openings 9PP, 9GG, and 9SS. In the present embodiment, during formation of the upper chip pad openings 9PP, 9GG, and 9SS, first and second upper power via-holes 9PL' and 9PL" and first and second upper ground via-holes 9GL' and 9GL" may be formed to expose the internal power lines 5PL' and 5PL" and the internal ground lines 5GL' and 5GL", respectively.

When the first dielectric layer 9 is formed of a polyimide layer, the first dielectric layer 9 may be patterned using conventional photolithography and etching processes. Alternatively, when the first dielectric layer 9 is formed of a photosensitive polyimide layer, the first dielectric layer 9 may be patterned using only a photolithography process without using an etching process.

The first lower power via-hole 7PL' and the first upper power via-hole 9PL' constitute a first power via-hole 10PL', and the second lower power via-hole 7PL" and the second upper power via-hole 9PL" constitute a second power via-hole 10PL". In addition, the first lower ground via-hole 7GL' and the first upper ground via-hole 9GL' constitute a first ground via-hole 10GL', and the second lower ground via-hole 7GL" and the second upper ground via-hole 9GL" constitute a second ground via-hole 10GL". Further, the lower power chip pad opening 7PP and the upper power chip pad opening 9PP constitute a power chip pad opening 10PP, and the lower ground chip pad opening 7GG and the upper ground chip pad opening 9GG constitute a ground chip pad opening 10GG. Furthermore, the lower signal chip pad opening 7SS and the upper signal chip pad opening 9SS constitute a signal chip pad opening 10SS.

A seed metal layer 11 is formed on the substrate 1 having the via-holes 10PL', 10PL", 10GL', and 10GL" and the chip pad openings 10PP, 10GG, and 10SS. The seed metal layer 11 may be formed by sequentially stacking a wetting metal layer and a copper layer. The wetting metal layer improves adhesion between the copper layer and the first dielectric layer 9. The wetting metal layer may be formed of a titanium layer or a chrome layer. The seed metal layer 11 may be formed using a sputtering technique.

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A sacrificial layer pattern **13** is formed on the seed metal layer **11**. The sacrificial layer pattern **13** may be formed of an insulating material pattern such as a photoresist pattern. The sacrificial layer pattern **13** may define first to third groove regions spaced apart from one another on the seed metal layer **11**. The first groove region exposes the power chip pad opening **10PP** and the power via-holes **10PL'** and **10PL''** as well as the seed metal layer **11** disposed therebetween, and the second groove region exposes the ground chip pad opening **10GG** and the ground via-holes **10GL'** and **10GL''** as well as the seed metal layer **11** disposed therebetween. In addition, the third groove region exposes at least the signal chip pad opening **10SS**.

Main metal patterns are formed on the exposed seed metal layer **11** using an electroplating method. That is, first to third main metal patterns are formed in the first to third grooves, respectively. The main metal patterns may be formed of a metal layer having a low resistivity. For example, the main metal patterns may be formed by sequentially plating a main metal layer and a cladding layer. The cladding layer may be formed by sequentially plating a diffusion barrier layer and a gold layer. The diffusion barrier layer is formed of a metal layer for suppressing interaction between the main metal layer and the gold layer, and the gold layer is formed to improve adhesion of a bonding wire during a subsequent bonding process. The main metal layer may be formed of a copper layer having a low resistivity, and the diffusion barrier layer may be formed of a nickel layer. As a result, a first main metal pattern **15PL** and a first cladding layer pattern **17PL**, which are sequentially stacked, may be formed on the seed metal layer **11** in the first groove region. A second main metal pattern **15GL** and a second cladding layer pattern **17GL**, which are sequentially stacked, may be formed on the seed metal layer **11** in the second groove region. In addition, a third main metal pattern **15SL** and a third cladding layer pattern **17SL**, which are sequentially stacked, may be formed on the seed metal layer **11** in the third groove region.

Referring to FIGS. **11A**, **11B**, and **11C**, the sacrificial layer pattern **13** is removed to expose the seed metal layer **11** thereunder. The exposed seed metal layer **11** is selectively etched to expose the first dielectric layer **9** thereunder. As a result, first to third seed metal patterns **11PL**, **11GL**, and **11SL** remain under the first to third main metal patterns **15PL**, **15GL**, and **15SL**, respectively. The first seed metal pattern **11PL**, the first main metal pattern **15PL** and the first cladding layer pattern **17PL** constitute a redistributed power line **18PL**. The second seed metal pattern **11GL**, the second main metal pattern **15GL**, and the second cladding layer pattern **17GL** constitute a redistributed ground line **18GL**. In addition, the third seed metal pattern **11SL**, the third main metal pattern **15SL**, and the third cladding layer pattern **17SL** constitute a redistributed signal line **18SL**.

Consequently, the redistributed power line **18PL** is formed to directly connect the internal power lines **5PL'** and **5PL''** to the power chip pad **5PP**, and the redistributed ground line **18GL** is formed to directly connect the internal ground lines **5GL'** and **5GL''** to the ground chip pad **5GG**. In addition, the redistributed signal line **18SL** is electrically connected to the signal chip pad **5SS**. The redistributed power line **18PL**, the redistributed ground line **18GL**, and the redistributed signal line **18SL** may have a plane shape or a mesh shape, when viewed from a plan view.

A second dielectric layer **19** is formed on the substrate **1** having the redistributed metal interconnections **18PL**, **18GL**, and **18SL**. The second dielectric layer **19** may be formed of the same material layer as the first dielectric layer **9**. The second dielectric layer **19** is patterned to form a power bond-

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ing pad opening **19PP**, a ground bonding pad opening **19GG**, and a signal bonding pad opening **19SS**, which expose the redistributed metal interconnections **18PL**, **18GL**, and **18SL**, respectively. As a result, the power bonding pad opening **19PP** defines a power bonding pad **18PP**, and the ground bonding pad opening **19GG** defines a ground bonding pad **18GG**. In addition, the signal bonding pad opening **19SS** defines a signal bonding pad **18SS**. The bonding pad openings **19PP**, **19GG**, and **19SS** may be formed spaced apart from the chip pads **5PP**, **5GG**, and **5SS**, respectively, as shown in FIGS. **11A**, **11B**, and **11C**. Alternatively, bonding pad openings **19PP**, **19GG** and **19SS** may be formed to overlap the chip pads **5PP**, **5GG**, and **5SS**, respectively, when viewed from a plan view.

The semiconductor chips shown in FIGS. **3** and **4** may be manufactured using the same or similar method as the embodiment described with reference to FIGS. **9A** to **11A**, **9B** to **11B**, and **9C** to **11C**. Therefore, methods of manufacturing the semiconductor chips shown in FIGS. **3** and **4** will not be described.

FIGS. **12** to **15** are cross-sectional views taken along line V-V' of FIG. **5** to illustrate methods of fabricating a semiconductor chip in accordance with another embodiment of the present invention.

Referring to FIG. **12**, an internal circuit (not shown) is formed on a semiconductor substrate **51**. The internal circuit may be formed using the same method as described with reference to FIGS. **9A**, **9B**, and **9C**. An interlayer insulating layer **53** is formed on the substrate **51** having the internal circuit. Chip pads and internal interconnections are formed on the interlayer insulating layer **53**. The internal interconnections may include first and second internal power supply lines **55GL** and **55PL** electrically connected to a first power supply terminal and a second power supply terminal of the internal circuit, respectively. In addition, the internal interconnections may further include at least one internal signal line (not shown) electrically connected to an input or output terminal of the internal circuit. The chip pads may include first and second power supply chip pads **55GG** and **55PP** electrically connected to the first and second internal power supply lines **55GL** and **55PL**, respectively.

The first and second internal power supply lines **55GL** and **55PL** may be an internal ground line and an internal power line, respectively. In this case, the first and second power supply chip pads **55GG** and **55PP** may be a ground chip pad and a power chip pad, respectively. On the contrary, the first and second internal power supply lines **55GL** and **55PL** may be an internal power line and an internal ground line, respectively. In this case, the first and second power supply chip pads **55GG** and **55PP** may be a power chip pad and a ground chip pad, respectively.

The internal power supply lines **55GL** and **55PL** may be formed using the same method as described with reference to FIGS. **9A**, **9B**, and **9C**. That is, at least one of the internal power supply lines **55PL** and **55GL** may be formed in or under the interlayer insulating layer **53**.

A passivation layer **57** is formed on the substrate **51** having the power supply chip pads **55GG** and **55PP**, the signal chip pad **55SS**, and the internal power supply lines **55GL** and **55PL**. The passivation layer **57** is patterned to form a first lower power supply chip pad opening **57GG**, a second lower power supply chip pad opening **57PP**, a lower signal chip pad opening **57SS**, a first lower via-hole **57GL** and a second lower via-hole **57PL** which expose the power supply chip pads **55GG** and **55PP**, the signal chip pad **55SS** and the internal power supply lines **55GL** and **55PL**, respectively.

A first lower dielectric layer **59** is formed on the substrate **51** having the lower power supply chip pad openings **57GG** and **57PP**, the lower signal chip pad opening **57SS**, and the lower via-holes **57GL** and **57PL**. The first lower dielectric layer **59** may be formed of the same material layer as the first dielectric layer **9** of FIGS. **10A**, **10B**, and **10C**. The first lower dielectric layer **59** is patterned to form a first upper power supply chip pad opening **59GG** and a first upper via-hole **59GL**, which expose the first power supply chip pad **55GG** and the first internal power supply line **55GL**, respectively. The first lower power supply chip pad opening **57GG** and the first upper power supply chip pad opening **59GG** constitute a first power supply chip pad opening **60GG**, and the first lower via-hole **57GL** and the first upper via-hole **59GL** constitute a first via-hole **60GL**.

Referring to FIG. **13**, a first redistributed power supply line **61GL** is formed on the first lower dielectric layer **59**. The first redistributed power supply line **61GL** is formed to directly connect the first internal power supply line **55GL** to the first power supply chip pad **55GG** through the first via-hole **60GL** and the first power supply chip pad opening **60GG**, respectively. The first redistributed power supply line **61GL** may be fabricated using the method of forming the redistributed metal interconnections **18PL**, **18GL**, and **18SL** described with reference to FIGS. **10A**, **10B**, **10C**, **11A**, **11B**, and **11C**. In addition, the first redistributed power supply line **61GL** may be formed to have a plane shape or a mesh shape, when viewed from a plan view.

A first upper dielectric layer **63** is formed over the first redistributed power supply line **61GL**. The first upper dielectric layer **63** may also be formed of the same material layer as the first dielectric layer **9** described with reference to FIGS. **10A**, **10B**, and **10C**.

Referring to FIG. **14**, the first upper/lower dielectric layers **63** and **59** are patterned to form a second upper power supply chip pad opening **63PP** and a second upper via-hole **63PL** which expose the second power supply chip pad **55PP** and the second internal power supply line **55PL**, respectively. The second lower power supply chip pad opening **57PP** and the second upper power supply chip pad opening **63PP** constitute a second power supply chip pad opening **64PP**, and the second lower via-hole **57PL** and the second upper via-hole **63PL** constitute a second via-hole **64PL**.

A second redistributed power supply line **65PL** is formed on the first upper dielectric layer **63**. The second redistributed power supply line **65PL** is formed to directly connect the second internal power supply line **55PL** to the second power supply chip pad **55PP** through the second via-hole **64PL** and the second power supply chip pad opening **64PP**, respectively. The second redistributed power supply line **65PL** may be fabricated using the method of forming a first redistributed power supply line **61GL**, i.e., an electroplating method. In addition, the second redistributed power supply line **65PL** may be formed to have a plane shape or a mesh shape, when viewed from a plan view.

When the first and second power supply chip pads **55GG** and **55PP** correspond to a ground chip pad and a power chip pad respectively, the first and second redistributed power supply lines **61GL** and **65PL** may act as a redistributed ground line and a redistributed power line, respectively. On the contrary, when the first and second power supply chip pads **55GG** and **55PP** correspond to a power chip pad and a ground chip pad respectively, the first and second redistributed power supply lines **61GL** and **65PL** may act as a redistributed power line and a redistributed ground line, respectively.

In the present embodiments, at least a portion of the first redistributed power supply line **61GL** may be formed to overlap at least a portion of the second redistributed power supply line **65PL**, as shown in FIG. **14**. In this case, power capacitance C_{pg} (see FIG. **6**) may be provided between the first and second redistributed power supply lines **61GL** and **65PL**. The power capacitance C_{pg} can improve power noise immunity. Therefore, in order to improve the power noise immunity, an overlap area between the first and second redistributed power supply lines **61GL** and **65PL** is preferably increased.

Referring to FIG. **15**, a second dielectric layer **67** is formed on the substrate **51** having the second redistributed power supply line **65PL**. The second dielectric layer **67** may be formed of a polymer layer such as a polyimide layer or a photosensitive polyimide layer. Alternatively, the second dielectric layer **67** may be formed of an oxide layer such as a silicon oxide layer. The first and second dielectric layers **63** and **67** are patterned to form a first bonding pad opening **67GG** and a second bonding pad opening **67PP**, which expose the first redistributed power supply line **61GL** and the second redistributed power supply line **65PL**, respectively. The first bonding pad opening **67GG** defines a first bonding pad **61GG**, and the second bonding pad opening **67PP** defines a second bonding pad **65PP**.

According to some embodiments of the present invention as described above, at least one redistributed power supply line is provided on a substrate having an internal circuit as well as an internal ground line and an internal power line, which are electrically connected to the internal circuit. The redistributed power supply line is directly connected to the internal ground line or the internal power line, thereby supplying stable power to the internal circuit through the redistributed power supply line.

Exemplary embodiments of the present invention have been disclosed herein and, although specific terms are employed, they are used and are to be interpreted in a generic and descriptive sense only and not for purpose of limitation. Accordingly, it will be understood by those of ordinary skill in the art that various changes in form and details may be made without departing from the spirit and scope of the present invention as set forth in the following claims.

What is claimed is:

1. A method of fabricating a semiconductor chip, the method comprising:

- forming an internal circuit on a semiconductor substrate;
- forming an internal interconnection electrically connected to the internal circuit;
- forming a chip pad electrically connected to the internal interconnection over the internal circuit;
- forming a passivation layer over the internal interconnection and the chip pad, the passivation layer having a via-hole and a chip pad opening that expose the internal interconnection and the chip pad, respectively; and
- forming a redistributed metal interconnection on the passivation layer, the redistributed metal interconnection being directly connected to the internal interconnection and the chip pad through the via-hole and the chip pad opening, respectively.

2. The method according to claim 1, wherein the internal circuit includes at least one of memory cells and a peripheral circuit of a semiconductor memory device.

3. The method according to claim 1, wherein the chip pad includes at least one of a ground chip pad and a power chip pad.

4. The method according to claim 1, wherein the passivation layer is formed by sequentially stacking a silicon oxide layer and a silicon nitride layer.

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5. The method according to claim 1, further comprising forming a first dielectric layer on the passivation layer before forming the redistributed metal interconnection, wherein the via-hole and the chip pad opening penetrate the passivation layer and the first dielectric layer.

6. The method according to claim 5, wherein the first dielectric layer is formed from at least one of a silicon oxide layer, a polyimide layer, and a photosensitive polyimide layer.

7. The method according to claim 1, wherein forming the redistributed metal interconnection comprises:

forming a seed metal layer on an exposed surface of the substrate having the via-hole and the chip pad opening;

forming a sacrificial layer pattern on the seed metal layer, the sacrificial layer pattern being formed to have a groove which exposes the seed metal layer in the via-hole and the chip pad opening as well as the seed metal layer on the passivation layer between the via-hole and the chip pad opening;

forming a main metal pattern on the seed metal layer exposed by the groove using an electroplating technique;

selectively removing the sacrificial layer pattern to expose the seed metal layer under the main metal pattern; and etching the exposed seed metal layer to expose the passivation layer.

8. The method according to claim 7, wherein the seed metal layer is formed using a sputtering method.

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9. The method according to claim 7, wherein the seed metal layer is formed by sequentially stacking a wetting layer and a copper layer.

10. The method according to claim 7, wherein the sacrificial layer pattern is a photoresist pattern.

11. The method according to claim 7, wherein the main metal pattern comprises a copper layer.

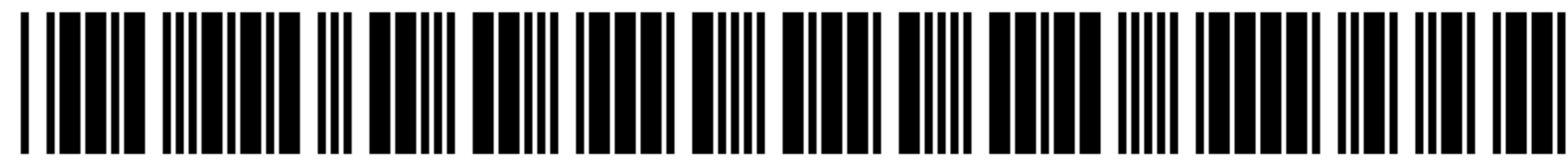
12. The method according to claim 7, wherein the main metal pattern is formed by sequentially stacking a copper layer, a diffusion barrier layer, and a gold layer, wherein the diffusion barrier layer comprises a metal layer for preventing interaction of the copper layer and the gold layer.

13. The method according to claim 5, further comprising: forming a second dielectric layer over the redistributed metal interconnection; and patterning the second dielectric layer to form a bonding pad opening that exposes a portion of the redistributed metal interconnection.

14. The method according to claim 13, wherein the second dielectric layer is formed from at least one of a silicon oxide layer, a polyimide layer, and a photosensitive polyimide layer.

15. The method according to claim 13, wherein the bonding pad opening overlaps the chip pad or is spaced apart from the chip pad when viewed from a plan view.

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(12) **EX PARTE REEXAMINATION CERTIFICATE** (12752nd)
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Lee

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(54) **SEMICONDUCTOR CHIPS HAVING REDISTRIBUTED POWER/GROUND LINES DIRECTLY CONNECTED TO POWER/GROUND LINES OF INTERNAL CIRCUITS AND METHODS OF FABRICATING THE SAME**

(2013.01); *H01L 2224/05552* (2013.01); *H01L 2224/05567* (2013.01); *H01L 2224/05571* (2013.01); *H01L 2924/00014* (2013.01); *H01L 2924/0002* (2013.01)

(75) Inventor: **Jong-Joo Lee**, Gyeonggi-do (KR)

(58) **Field of Classification Search**
None
See application file for complete search history.

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(56) **References Cited**

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To view the complete listing of prior art documents cited during the proceeding for Reexamination Control Number 90/015,298, please refer to the USPTO's Patent Electronic System.

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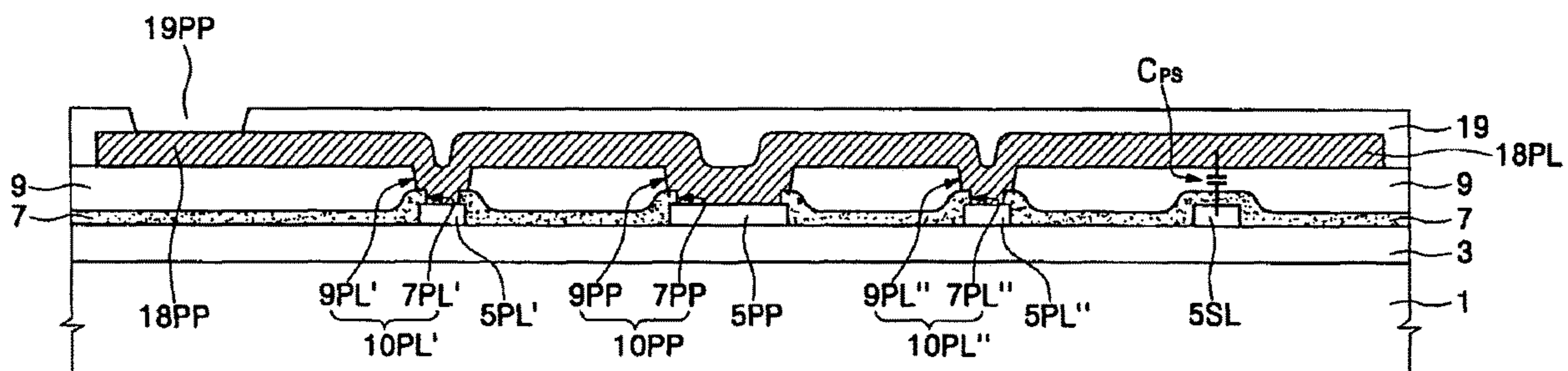
Mar. 18, 2005 (KR) 10-2005-0022787

(57) **ABSTRACT**

Provided are embodiments of semiconductor chips having a redistributed metal interconnection directly connected to power/ground lines of an internal circuit are provided. Embodiments of the semiconductor chips include an internal circuit formed on a semiconductor substrate. A chip pad is disposed on the semiconductor substrate. The chip pad is electrically connected to the internal circuit through an internal interconnection. A passivation layer is provided over the chip pad. A redistributed metal interconnection is provided on the passivation layer. The redistributed metal interconnection directly connects the internal interconnection to the chip pad through a via-hole and a chip pad opening, which penetrate at least the passivation layer. Methods of fabricating the semiconductor chip are also provided.

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H10B 12/00 (2023.01)
H01L 21/84 (2006.01)
H01L 23/528 (2006.01)
H01L 27/12 (2006.01)

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CPC *H10B 12/09* (2023.02); *H01L 21/84* (2013.01); *H01L 23/5286* (2013.01); *H01L 27/1203* (2013.01); *H01L 2224/05548*



**EX PARTE
REEXAMINATION CERTIFICATE**

THE PATENT IS HEREBY AMENDED AS 5
INDICATED BELOW.

AS A RESULT OF REEXAMINATION, IT HAS BEEN
DETERMINED THAT:

The patentability of claim **12** is confirmed. 10
Claims **1-11** and **13-15** are cancelled.

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